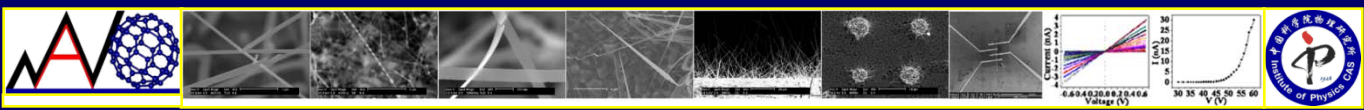


# Boron Nanowires for Flexible Electronics and Field Emission

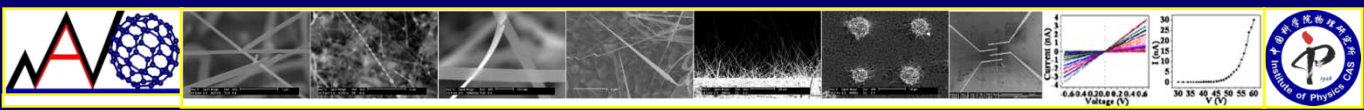
Hongjun Gao and Jifa Tian

*Institute of Physics, CAS, Beijing, China*



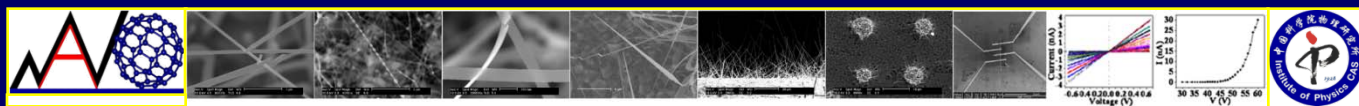
# OUTLINE

- Introduction
- Four Probe STM Setup: Imaging and I-V Measurements
- Boron Nanostructures: synthesis and characterization
- Properties of Boron Structures: electrical, mechanical and field emission
- Conclusions



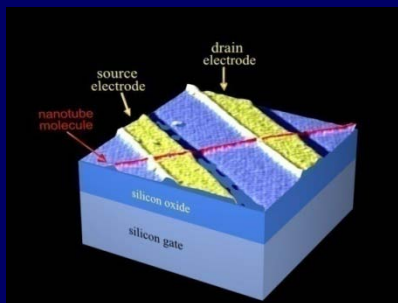
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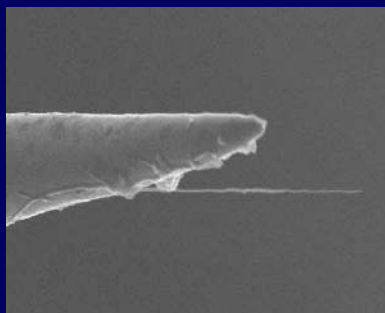


# 1D Semiconductor Nanostructures

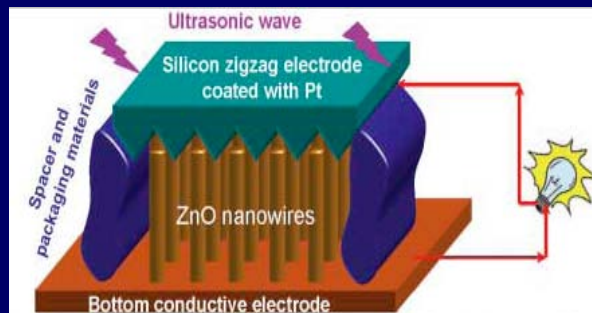
- **Nanotechnology:** Work at the atomic, molecular and supramolecular levels, in order to understand and create materials, devices and systems with fundamentally new properties and functions because of their small structures.
- **1D nanostructures:** 1/1000 the size of a human hair, high surface area to volume ratio, ranges from 10 nm to 100 nm in diameter
- **Synthesis techniques:** laser ablation, CVD, MOVPE, CBE, MBE...
- **Applications:** Nanotransistors, field emitters, energy and charge Storage ...



Nature 393 (1998)



IPN CNT group



Science 316 (2207)

# Flexible Technology and Field Emission



Circuits

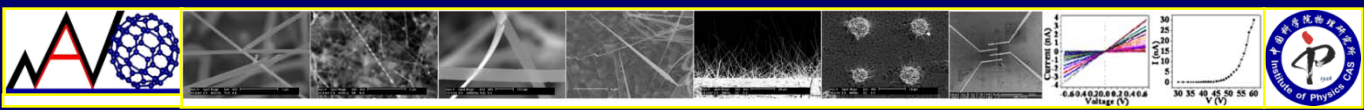


Displays

Flexible nanomaterials: **inorganic semiconductors** and **organic conducting materials**.

**Challenge:** (1) The high-performance inorganic electronic materials such as silicon tend to fracture under 1% tensile strain. (2) Carbon nanotubes have shown great promise for applications in flexible electronics, ill control of structural chirality makes them a big challenge for being useful in high-performance integrated circuits.

**New materials and techniques need to be developed!**

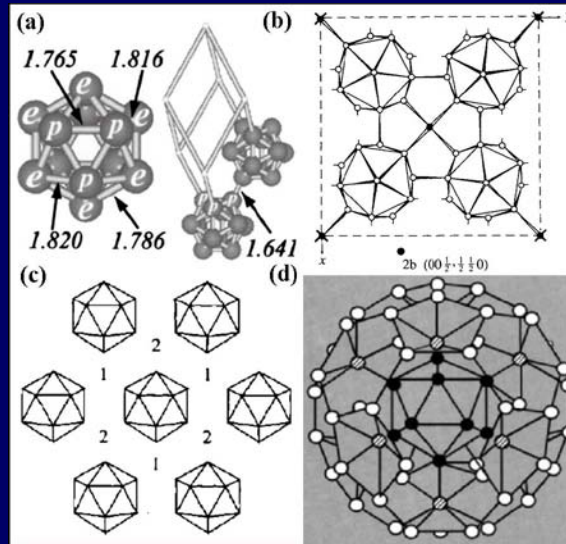


# Boron

## Properties:

- **Low** density ,  $2.364 \text{ g/cm}^3$  ;
- **High melting point** ,  $2300 \text{ }^\circ\text{C}$  ;
- **Large** bulk Young's modulus of  $380\text{--}400 \text{ GPa}$
- **Extreme** hardness close to diamond
- **Only** non-metallic element that has fewer than 4 electrons in its outer shell ;
- **Unusual** three-center  $sp^2$  hybrid valence bond
- Electron configuration is  $1s^2 2s^2 2p^1$
- Poor conductor at room temp but good at high temps

## Structures:



(a)  $B_{12}$  icosahedron

(b) Tetragonal B

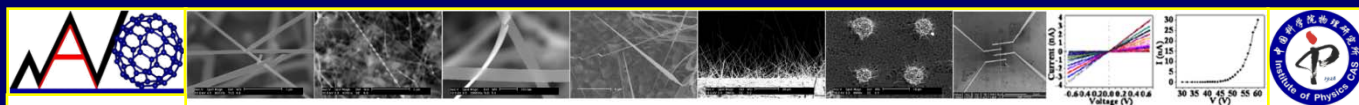
(c)  $\alpha$ - rhombohedral B

(d)  $\beta$ - rhombohedral B

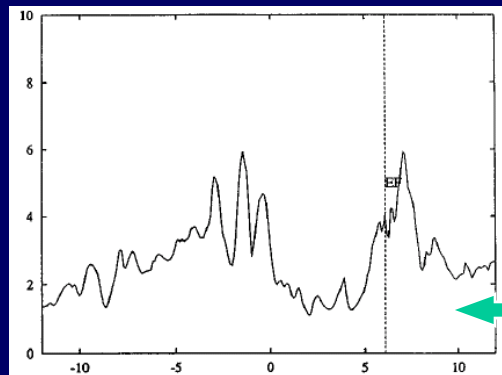
## Applications:

- **Lightweight coating** ;
- **High-temperature semiconductor devices** ;
- **Neutron absorbent** ;
- **Surface catalyst**

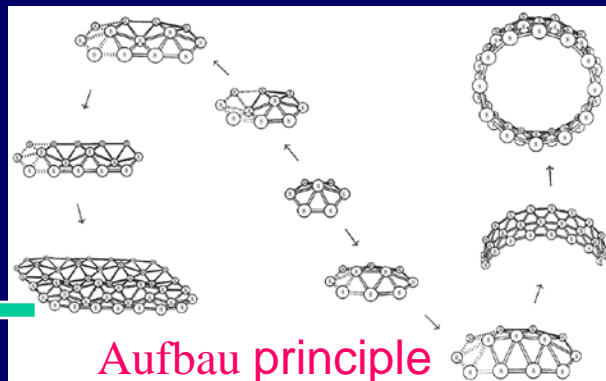




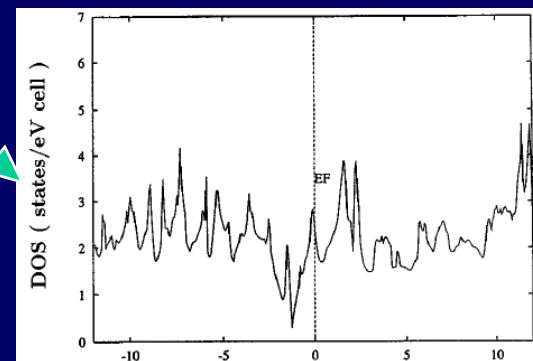
# Theoretical Work on Boron Nanostructures



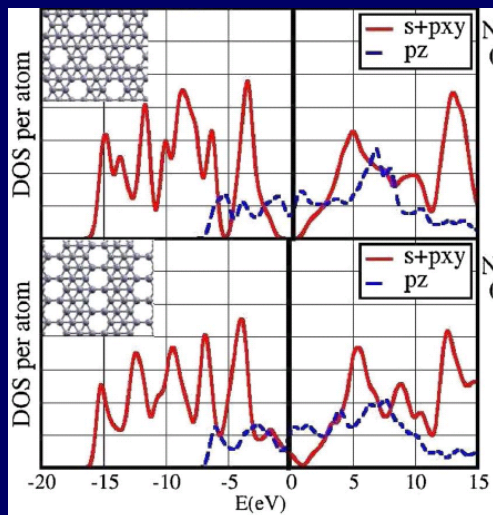
J. Chem. Phys. 110 (1999) 3176



Boron NT and sheet can be formed by B<sub>7</sub> cluster.

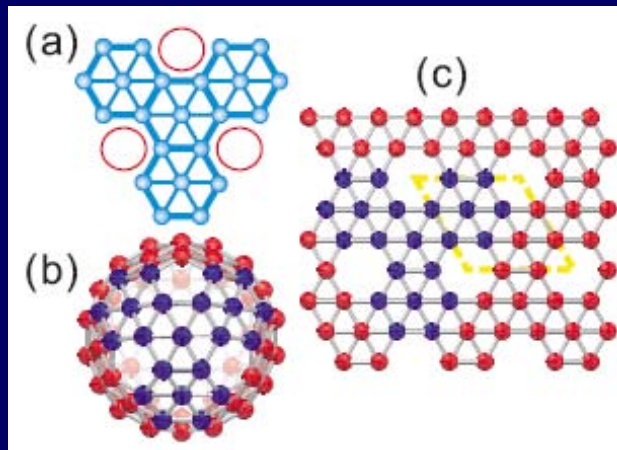


ChemPhysChem 6 (2005) 2001

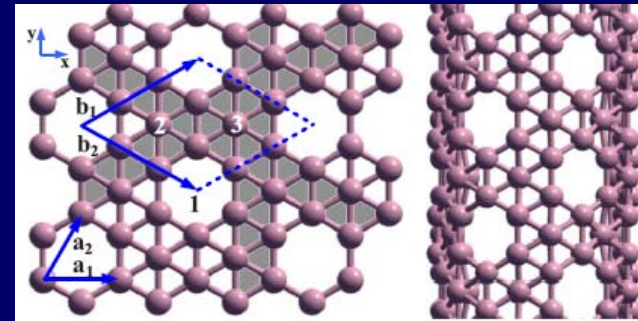


**Chirality**

PRL 99 (2007) 115501

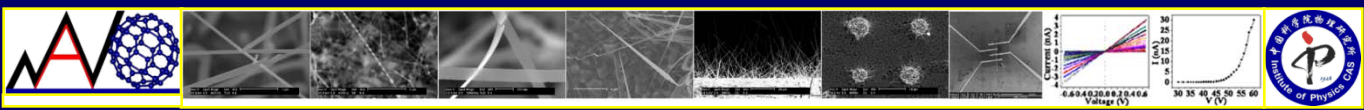


PRB 78 (2008) 201401

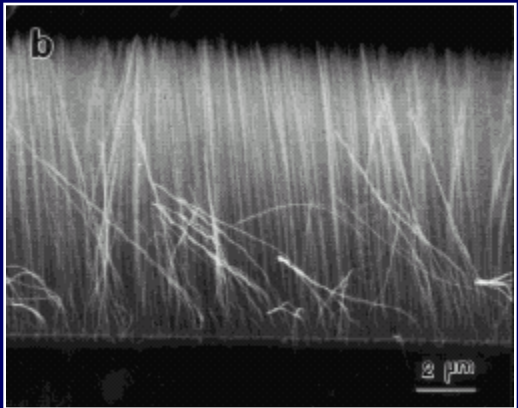


PRB 77 (2008) 041402

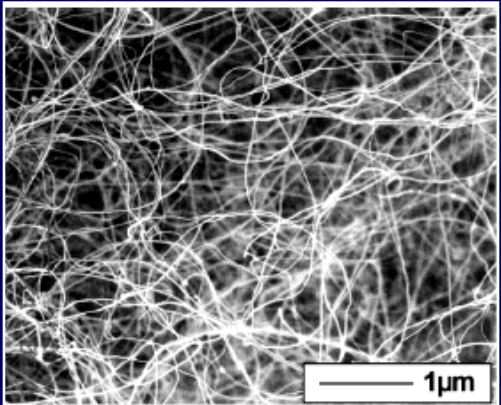
**Can boron nanotube be synthesized?**



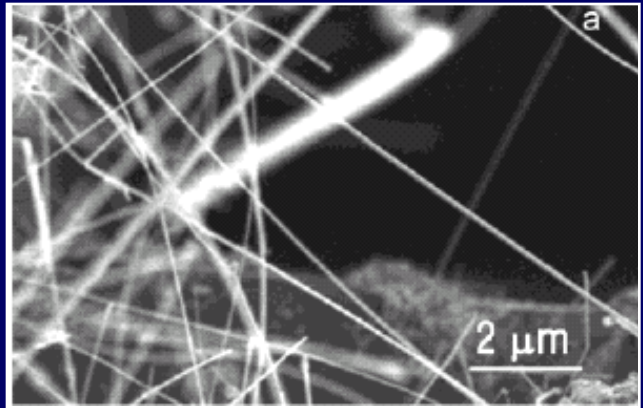
# Experimental Work on 1D Boron



Adv. Mater. 2001 13 1701



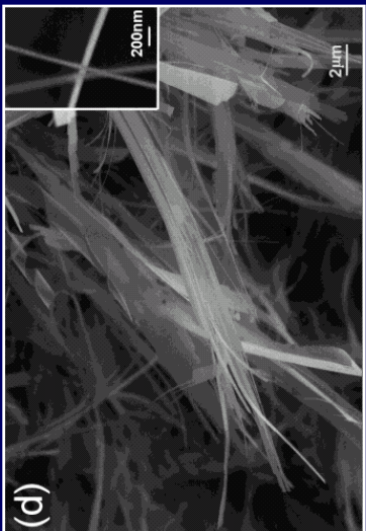
Adv. Mater. 2001 13 1487



J Am. Chem. Soc. 2002 124 4564



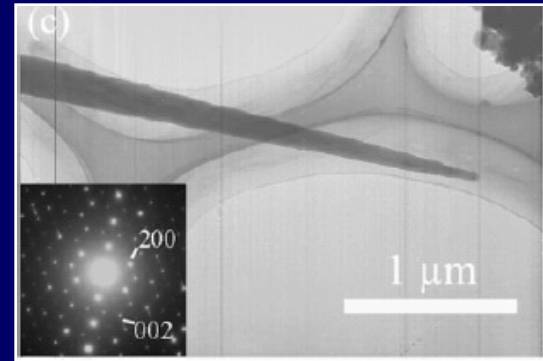
Chem. Comm. 2002 2806



Nano Lett 2004 4 963

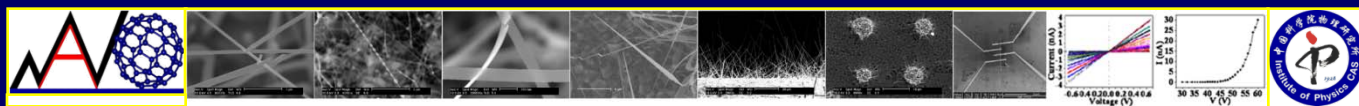


Nano Lett 2006 6 385

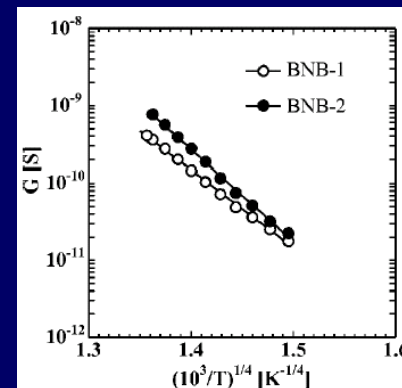
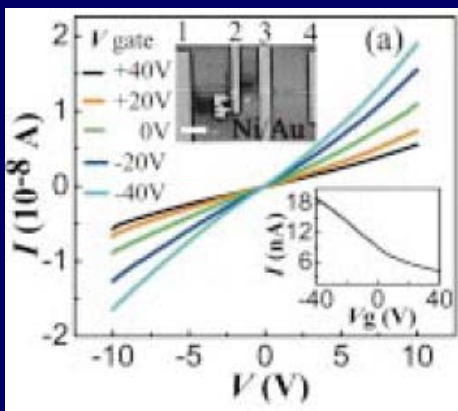
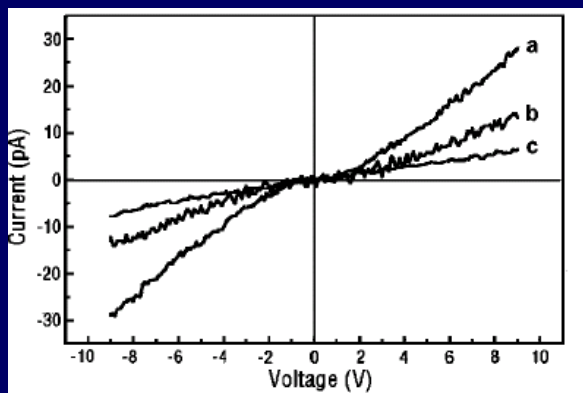


H. J. Gao *et al.*  
Adv. Mater 2007 19 4480





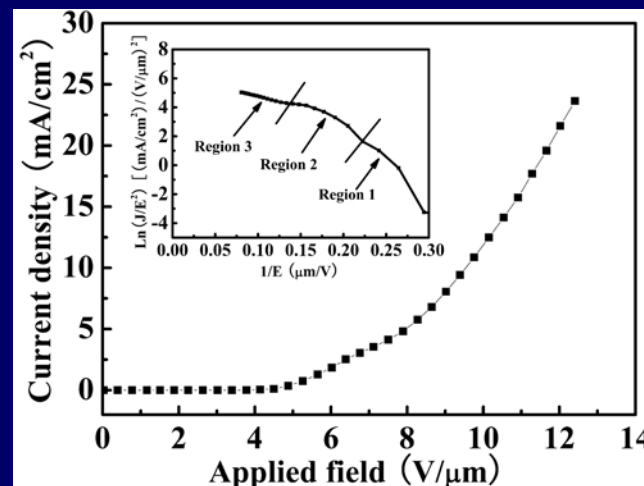
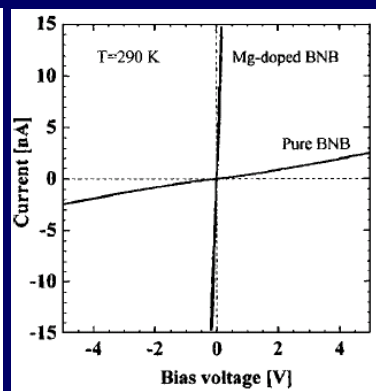
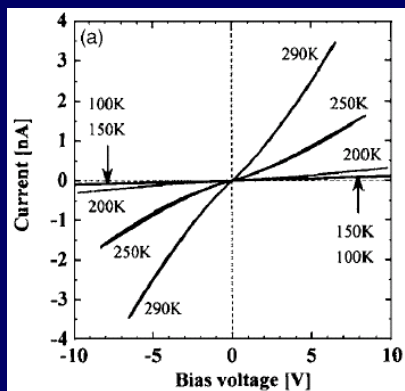
# Properties of Boron Nanostructures



J AM CHEM SOC 2002 124 4564

Appl. Phys. Lett. 2003 83 5280

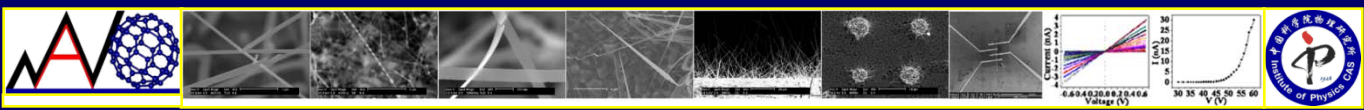
Appl. Phys. Lett. **86**, 212101 (2005)



J. Vac. Sci. Technol. B 23 2005 2510

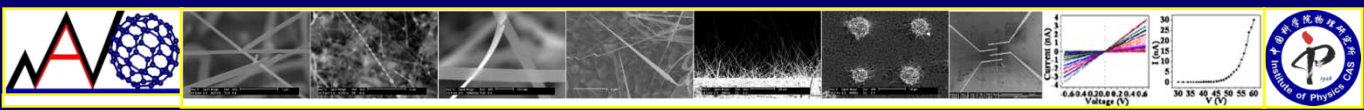
H. J. Gao *et al.* Adv. Mater 2007 19 4480

2009 Frontiers of Characterization and Metrology for Nanoelectronics, NY, May 11- 15, 2009



# OUTLINE

- Introduction
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# MBE-FSTM Combined System

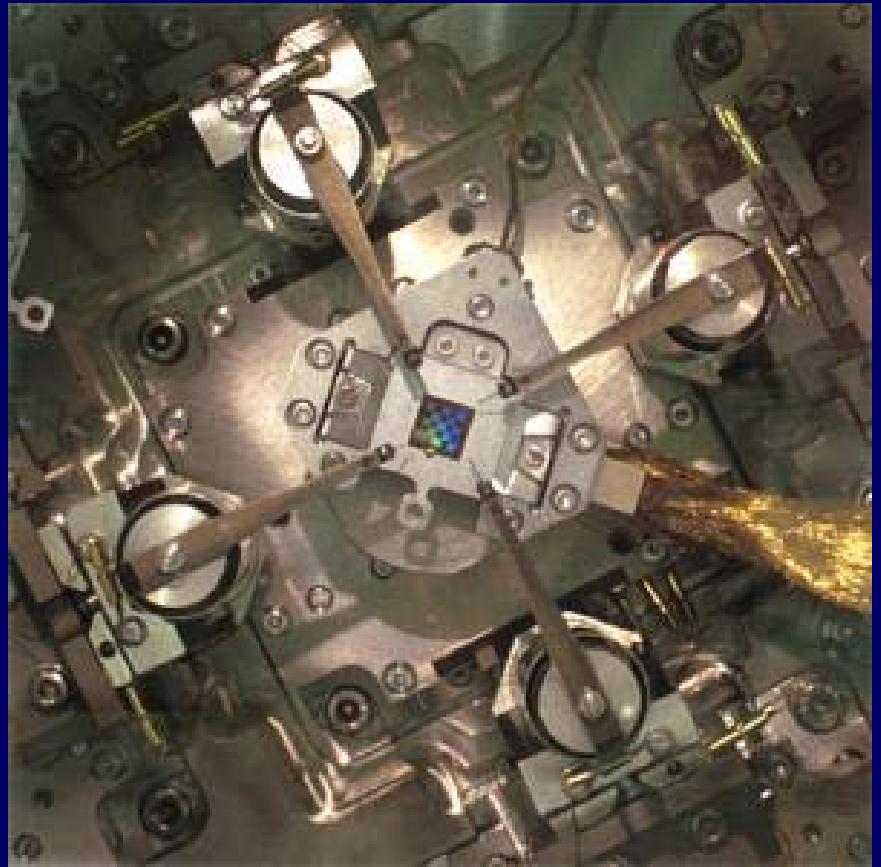
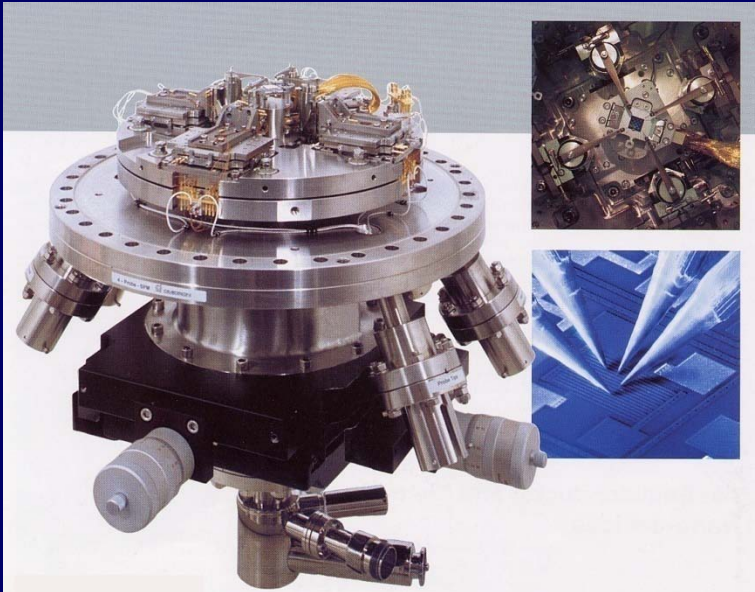


MBE



Four probe STM

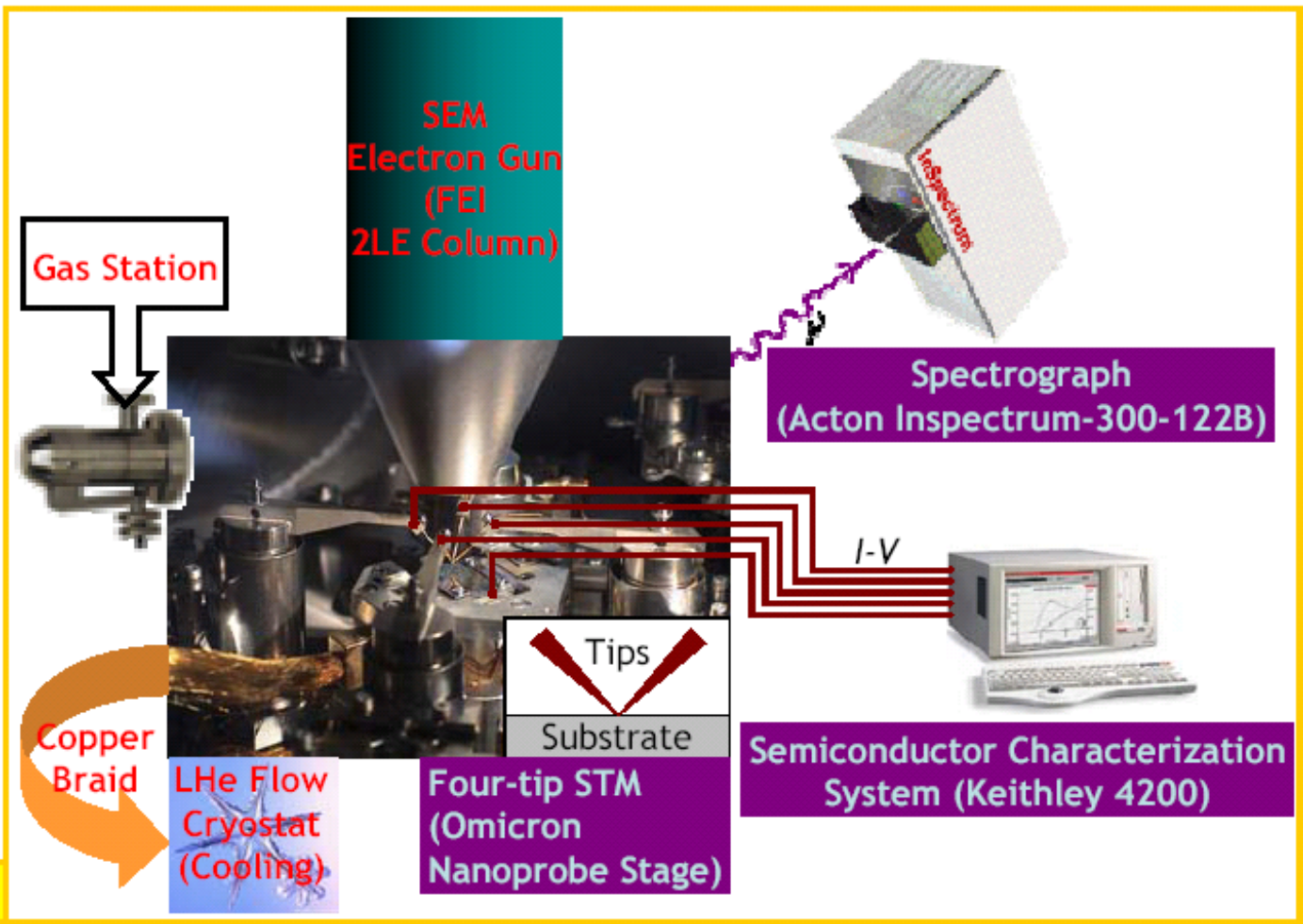
# Nanoprobe Stage

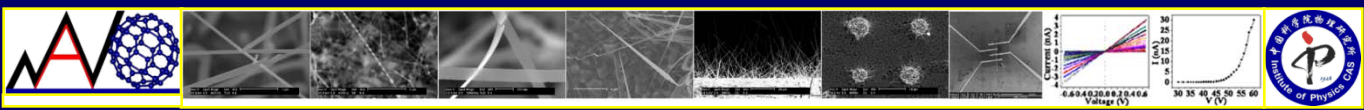


- Four independent STMs
- Atomic resolution (with IDE air spring)
- Temperature: from 30K to 500K (with CryoVac)



# Four Probe STM System



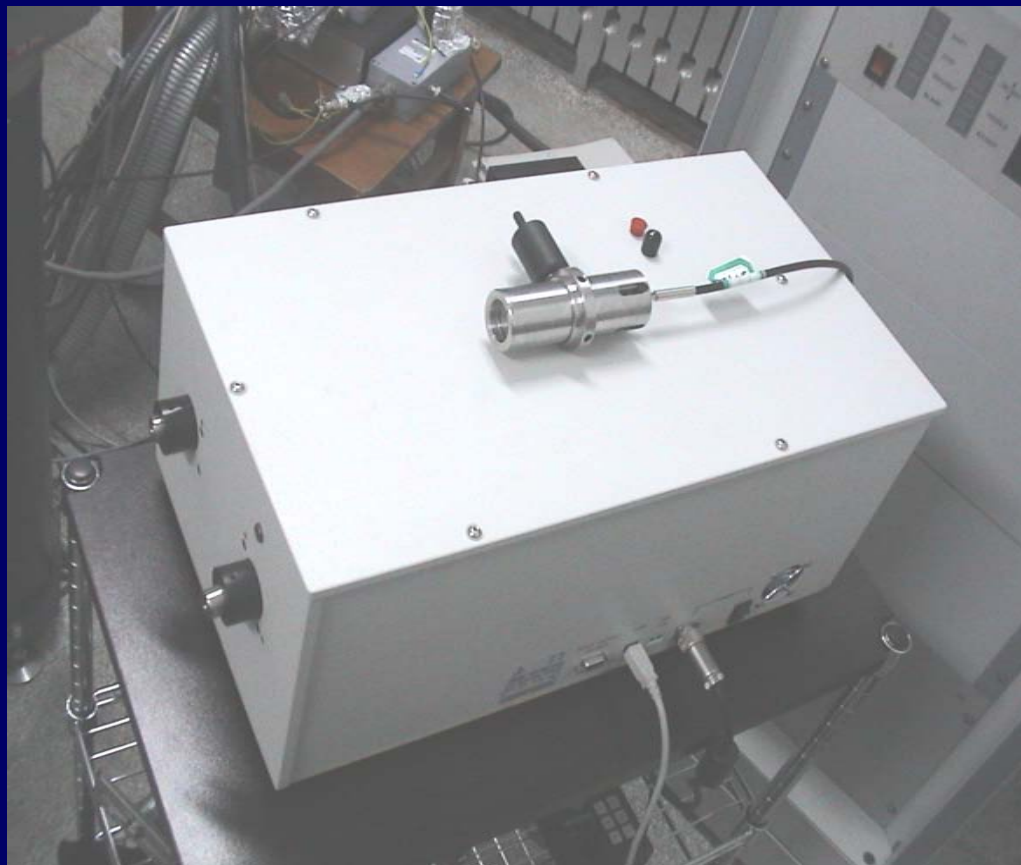


# I-V Measurements with Keithley SCS-4200



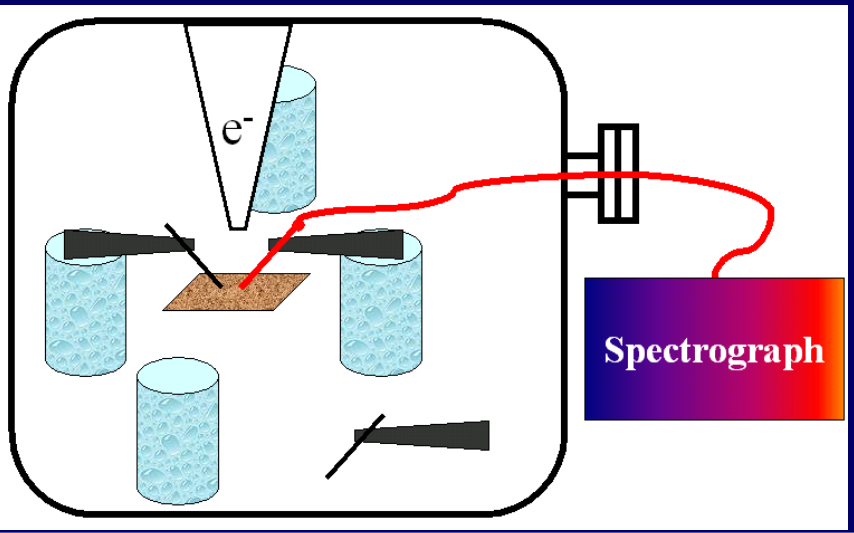
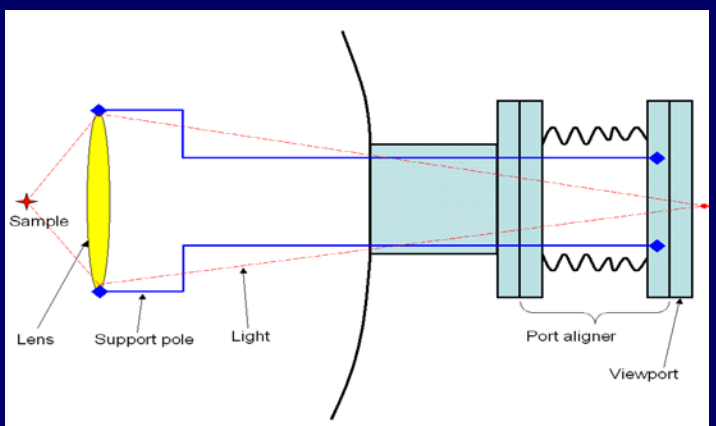
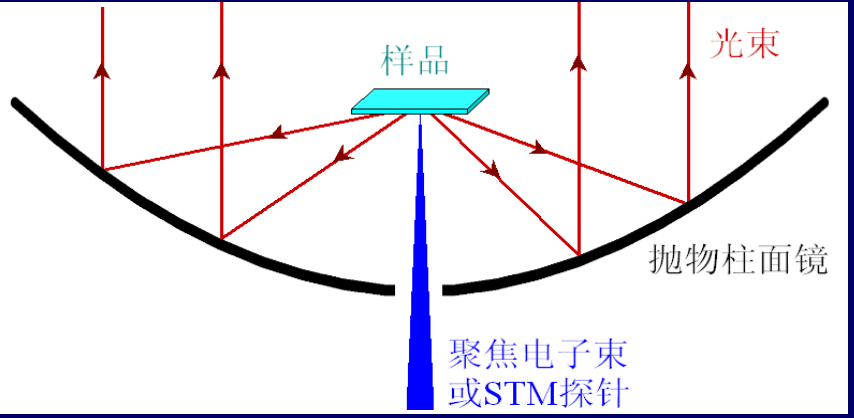
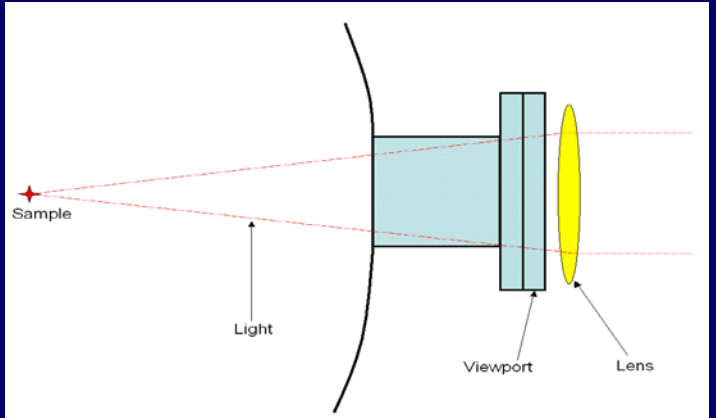
- Three independent source-measure units (SMUs) and their preamplifiers (PAs)
- Common ground unit (GNDU)
- Capable for four-terminal-method
- Current resolution:  $1\text{E}-15\text{A}$

# Optical Property Measurements with Acton Inspectrum-300-122B

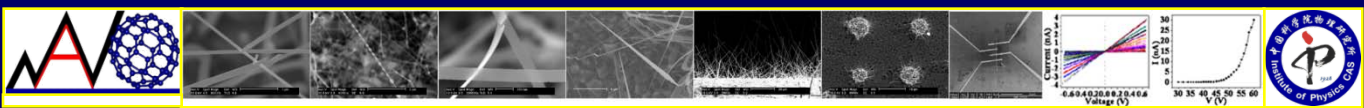


- Wavelength: 200 ~ 900nm
- Resolution: 0.2nm
- CL spectrum (SEM) & tunneling current induced photon emission (STM)
- Others after slight alteration in inducing source

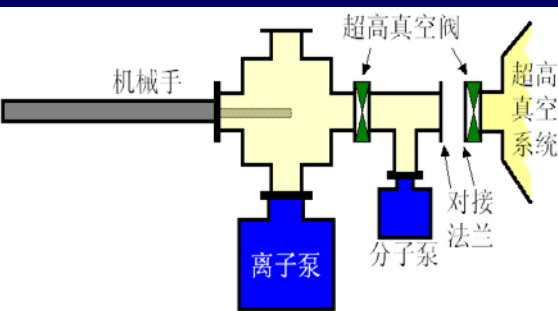
# Optical Measurements Setup

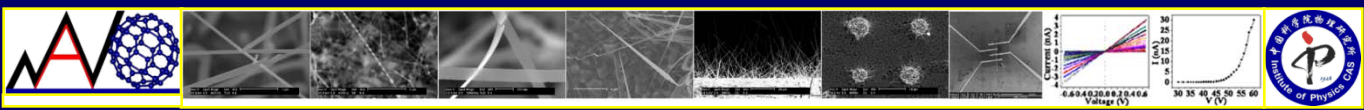




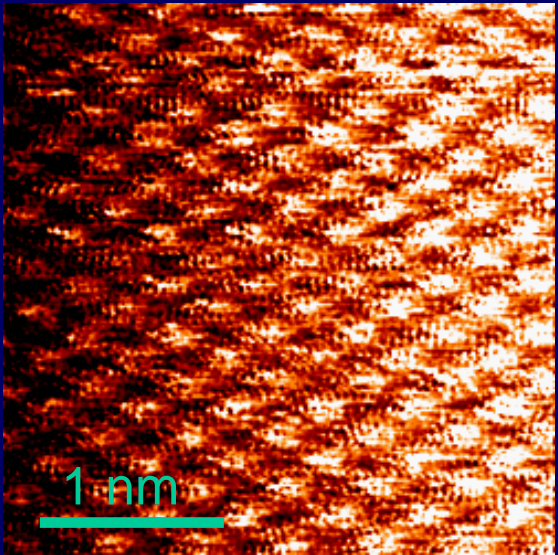


# Vacuum System and Other UHV-MBE-STMs

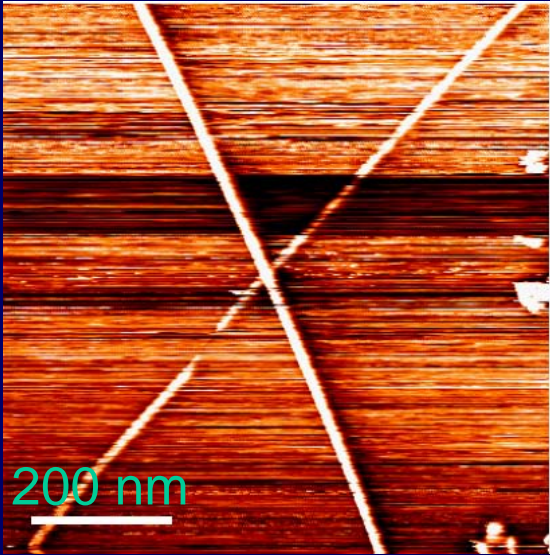




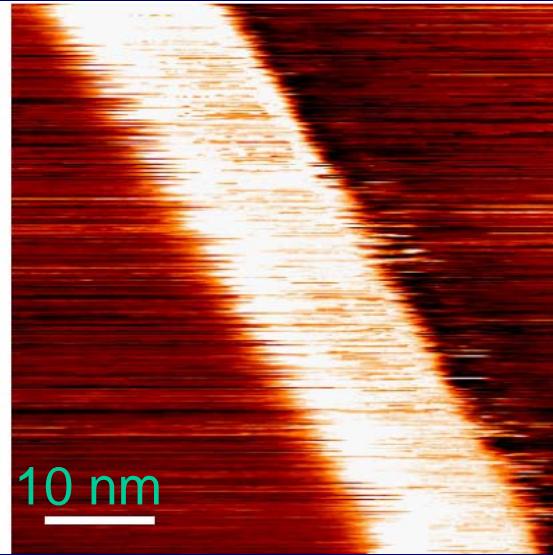
# STM Imaging: Atomic Resolution Capability

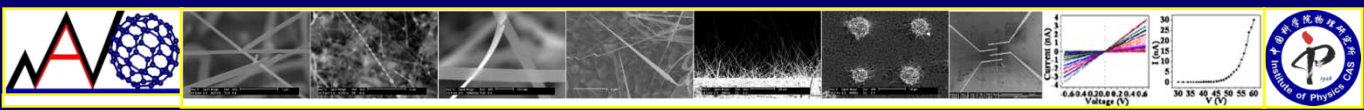


HOPG  
 $I=500\text{pA}$ ,  $V=70\text{mV}$

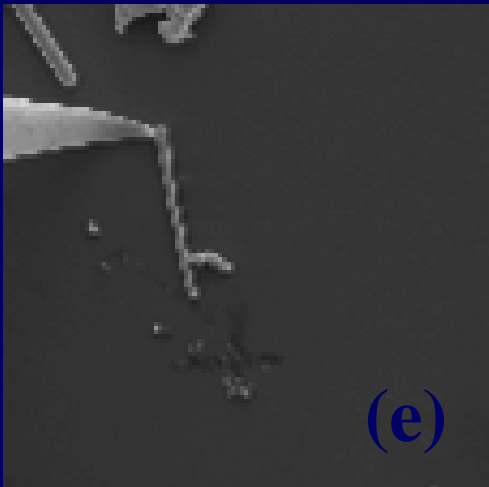
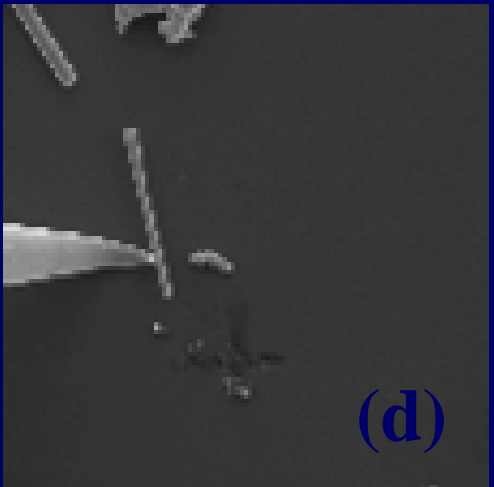
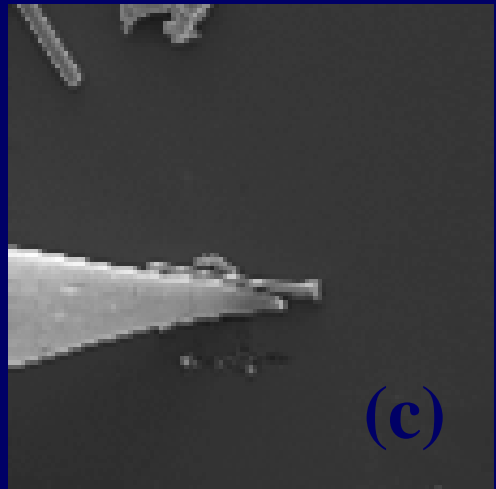
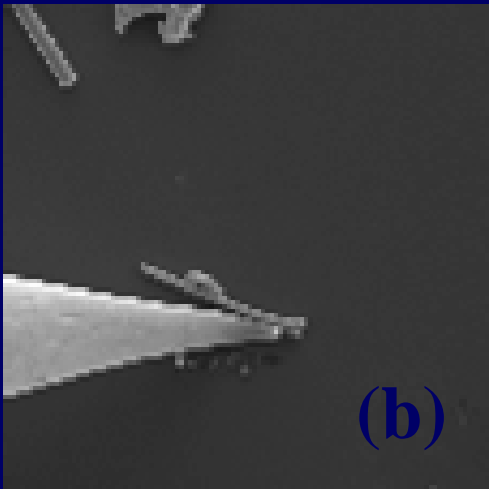
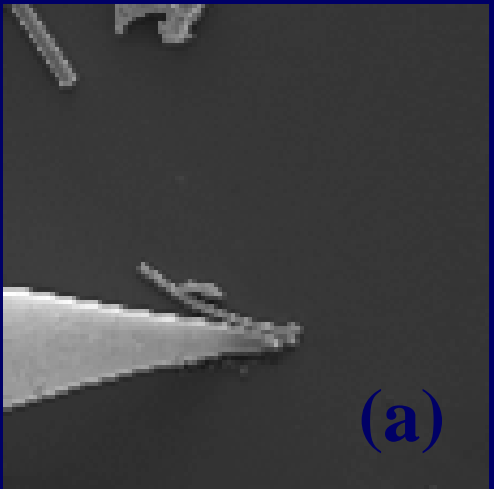


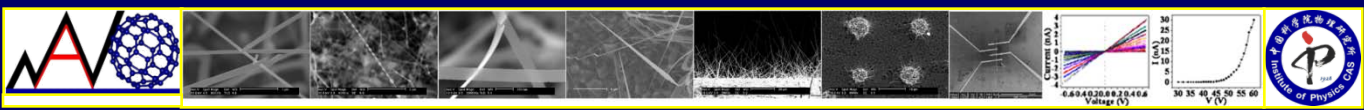
B nanowire on HOPG  
 $I=500\text{pA}$ ,  $V=300\text{mV}$



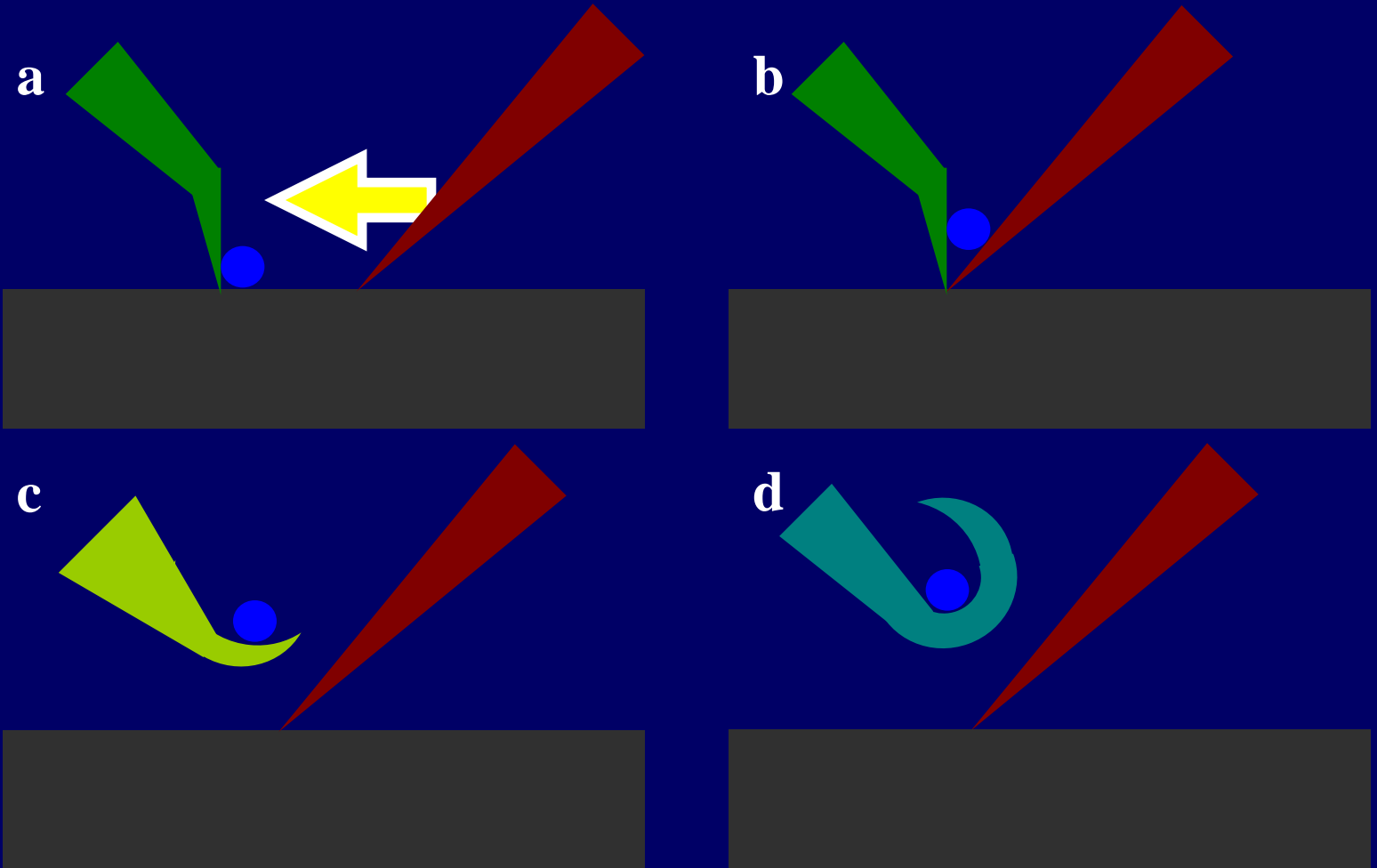


# Manipulation of Nanowires: Pushing

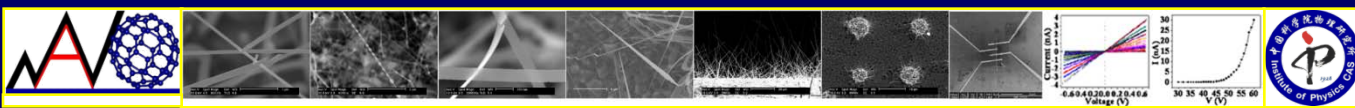




# Manipulation of Nanowires: Hocking



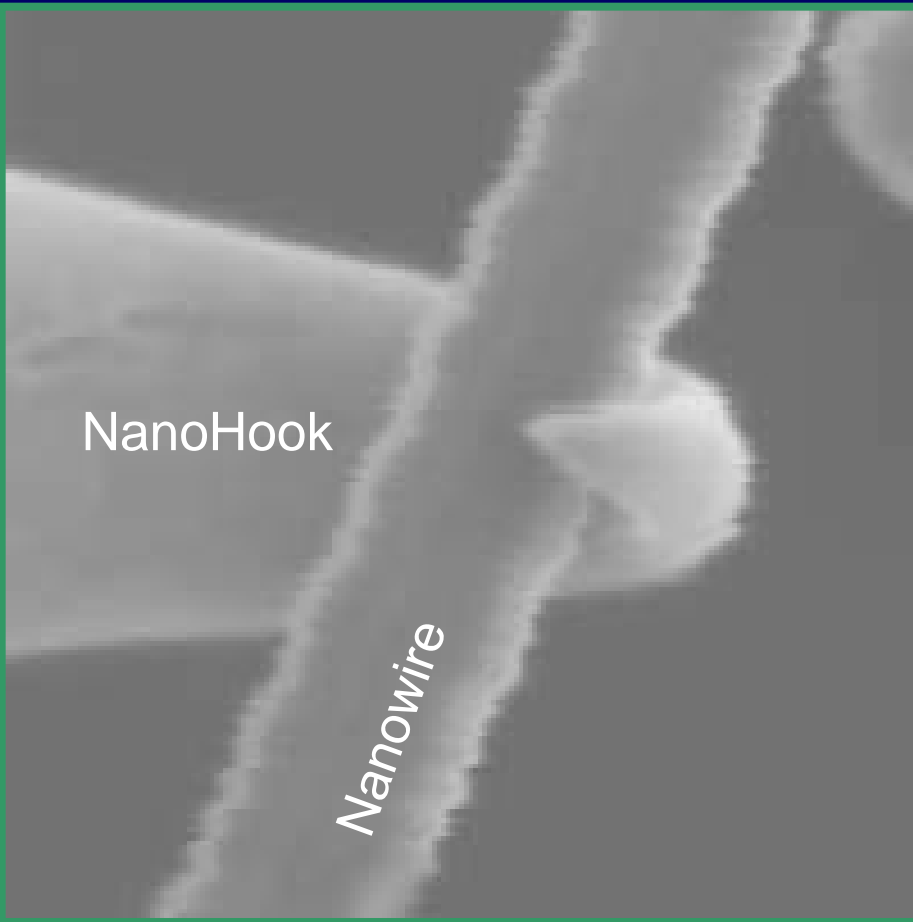




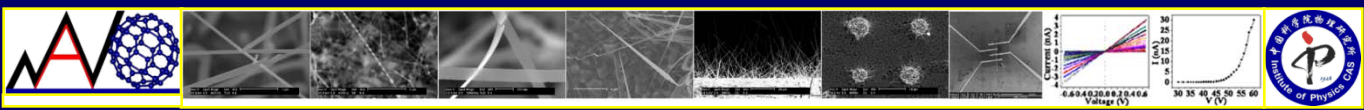
# Manipulation of Nanowires: Hocking



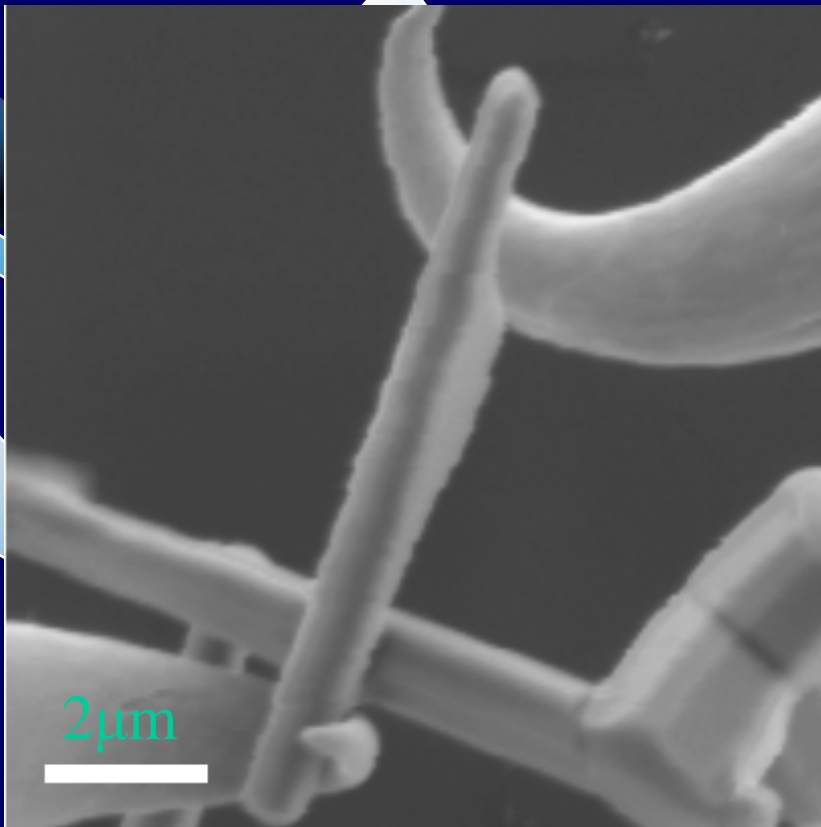
SEM image:  $7\mu\text{m} \times 7\mu\text{m}$

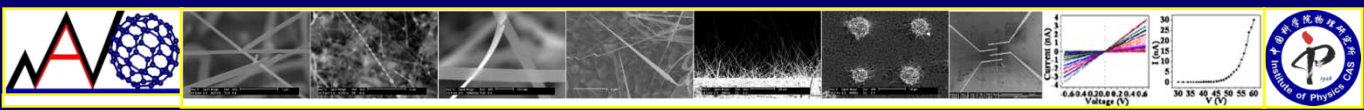


SEM image:  $2\mu\text{m} \times 2\mu\text{m}$

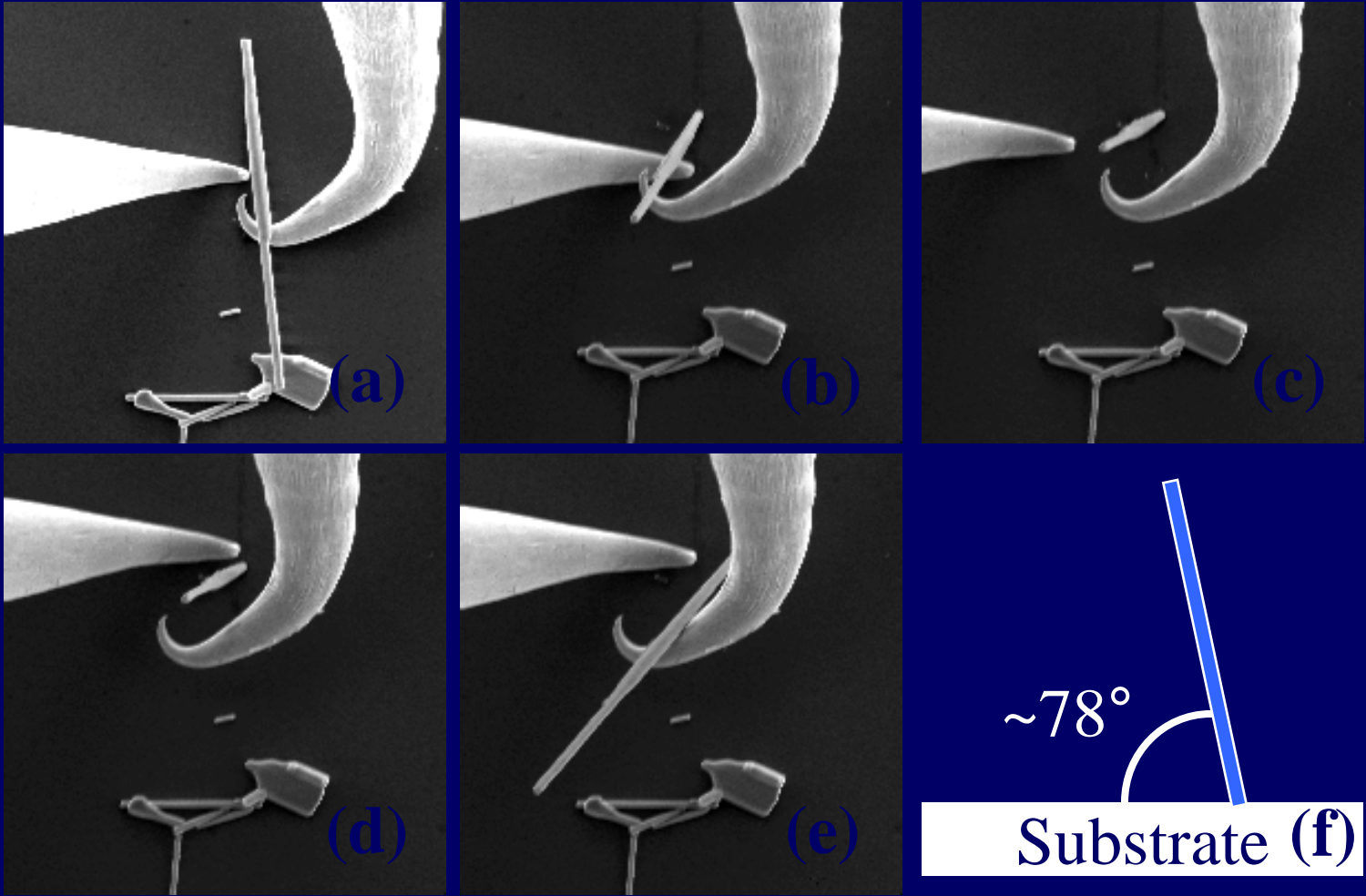


# Manipulation of Nanowires and I-V Measurements

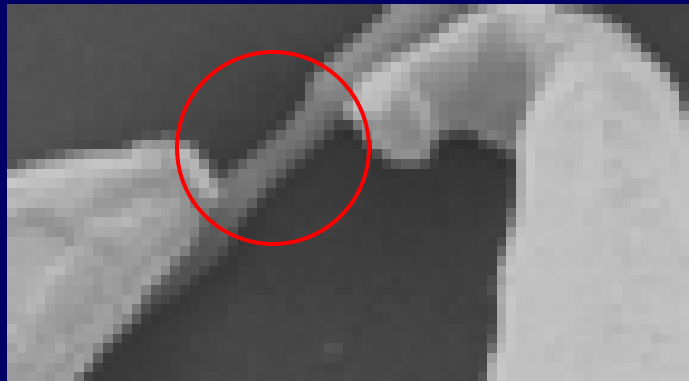
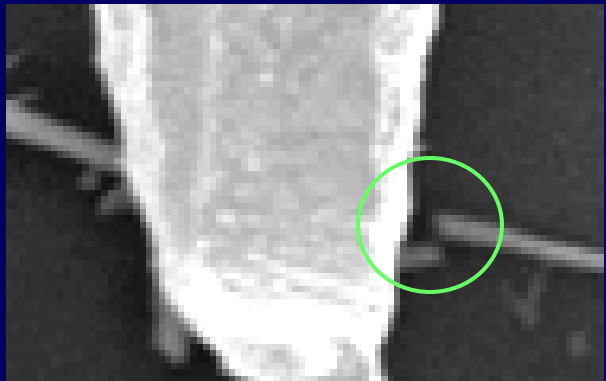
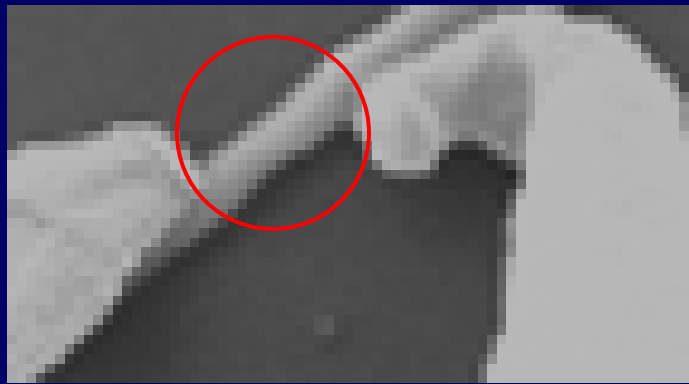
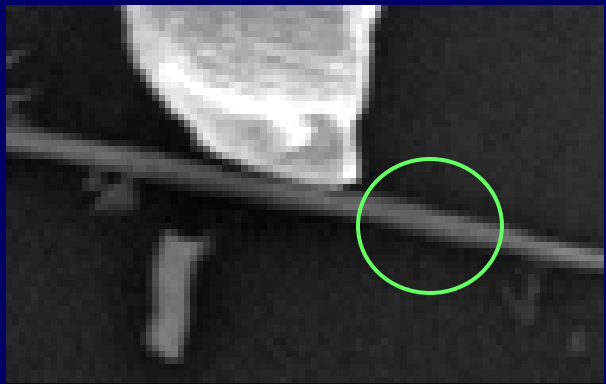




# Manipulation of Nanowires: I-V Measurements



# Manipulation of Nanowires: Cutting and Annealing

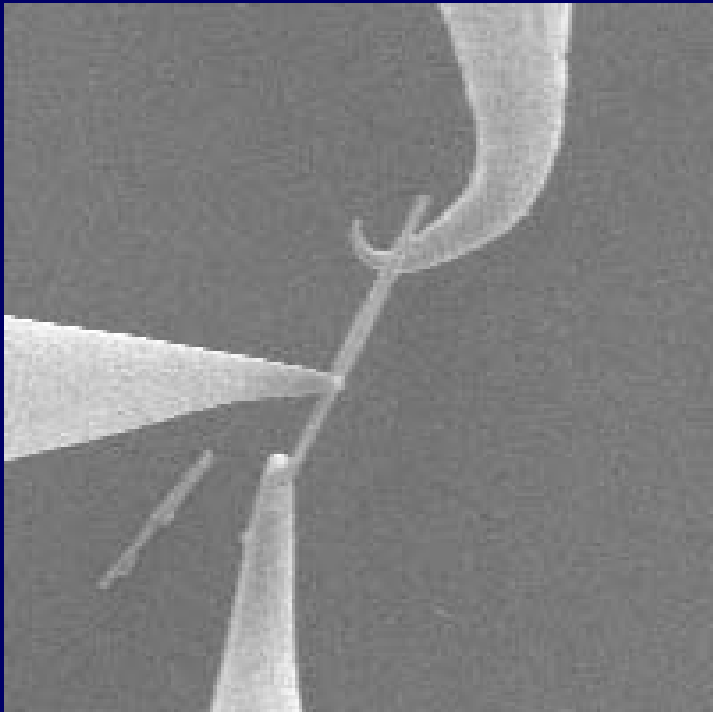


Cutting

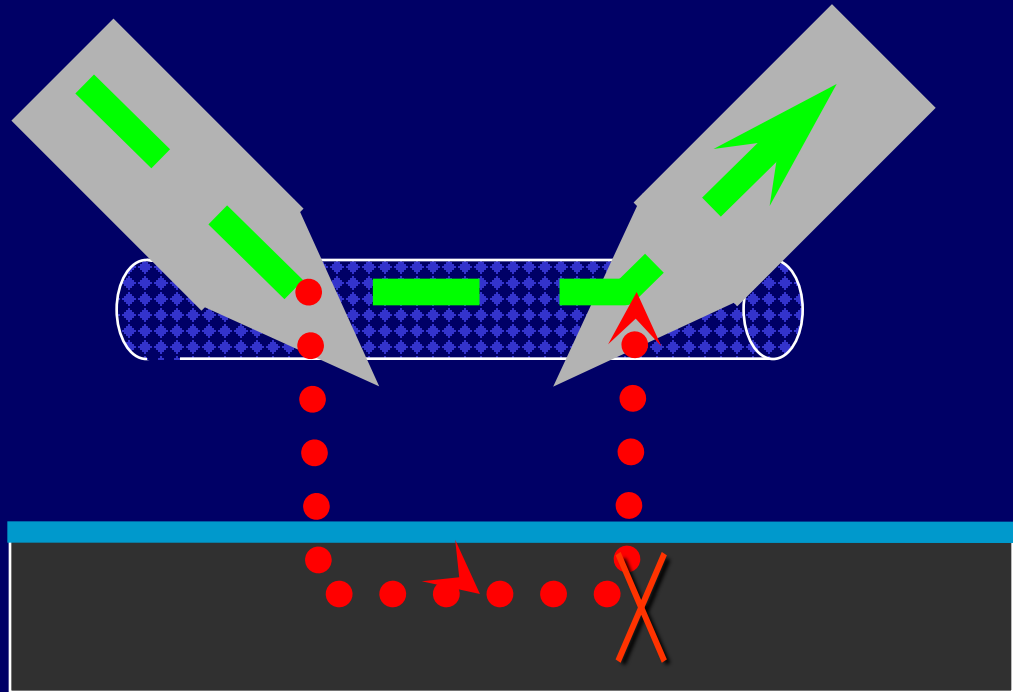
Sublimation



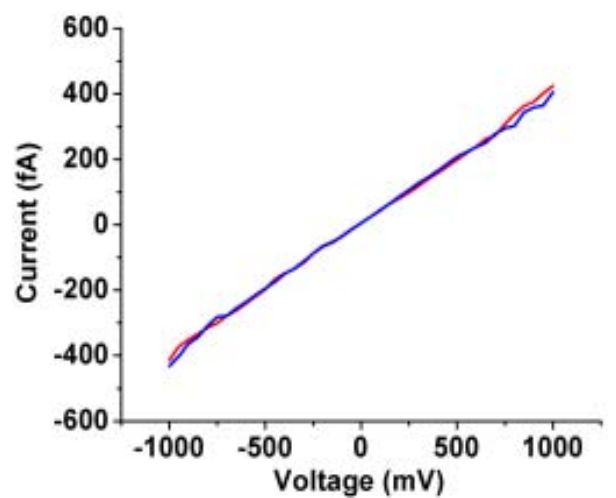
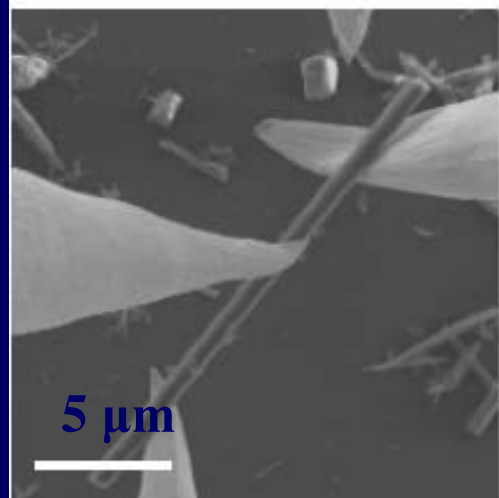
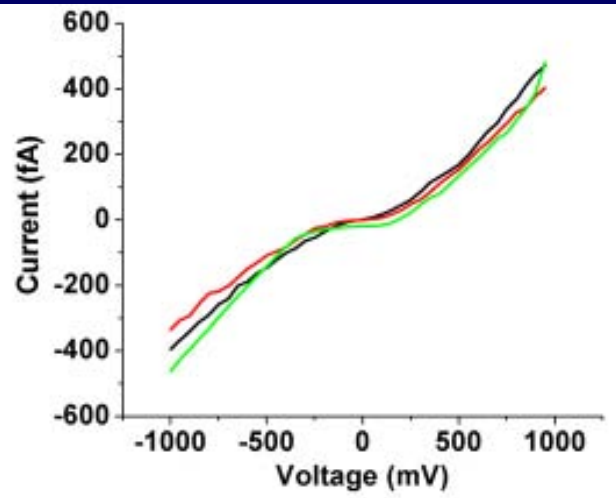
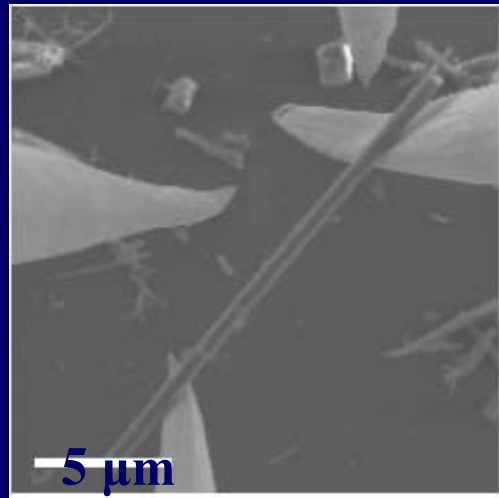
# Manipulation of Nanowires: I-V Measurements

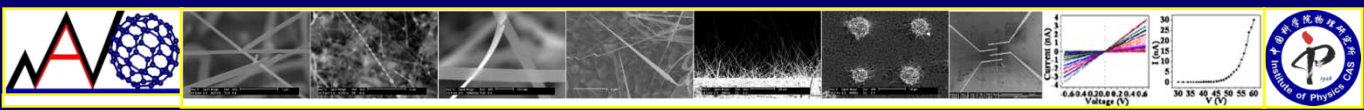


SEM image:  $25\mu\text{m} \times 25\mu\text{m}$

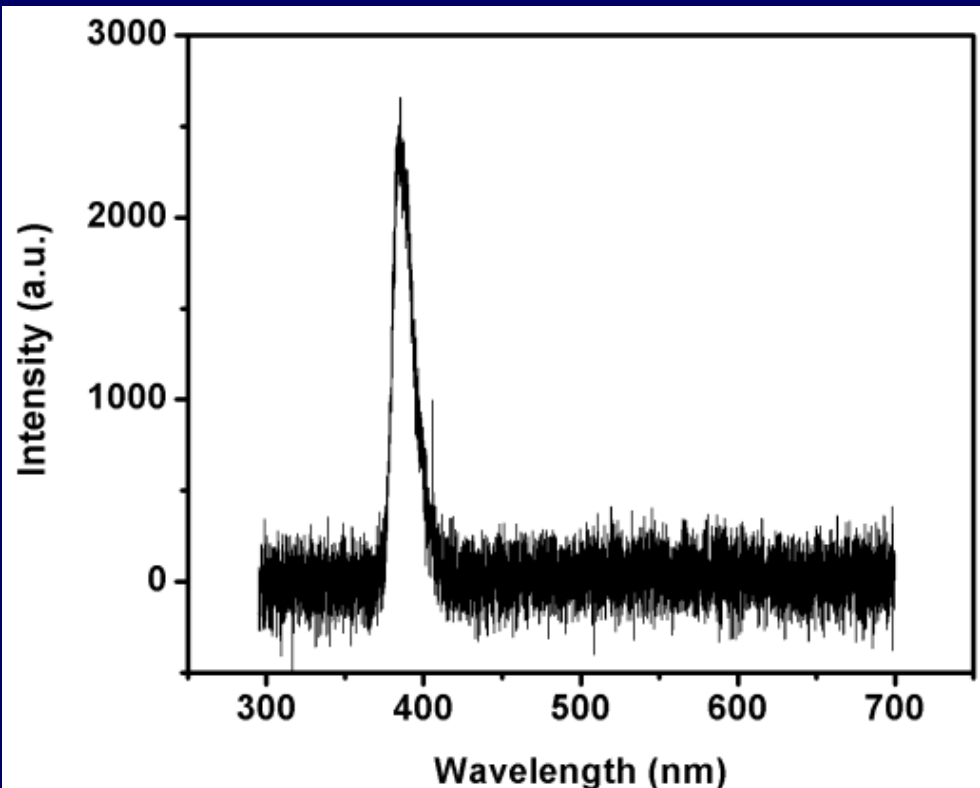
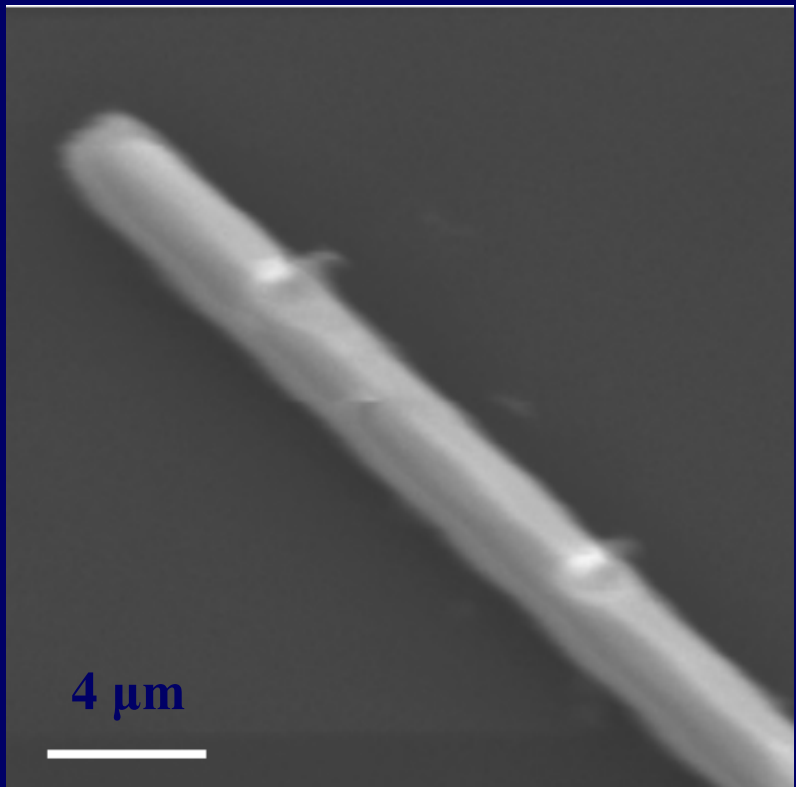


# Manipulation of Nanowires: I-V measurements

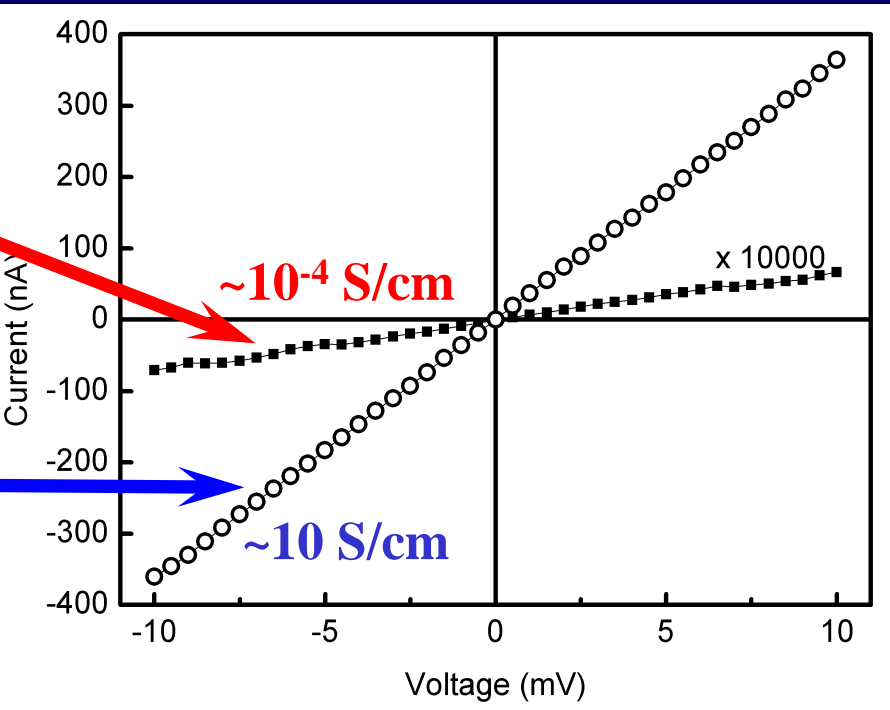
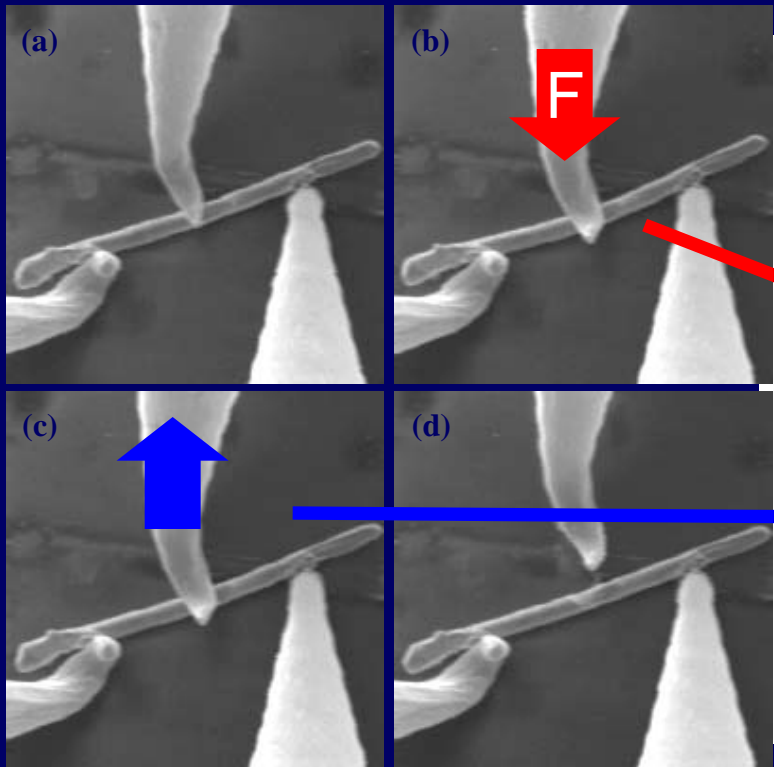




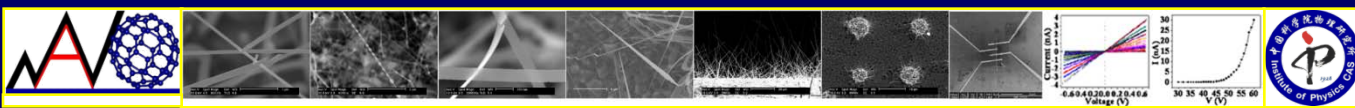
# CL Property of ZnO Nanowires



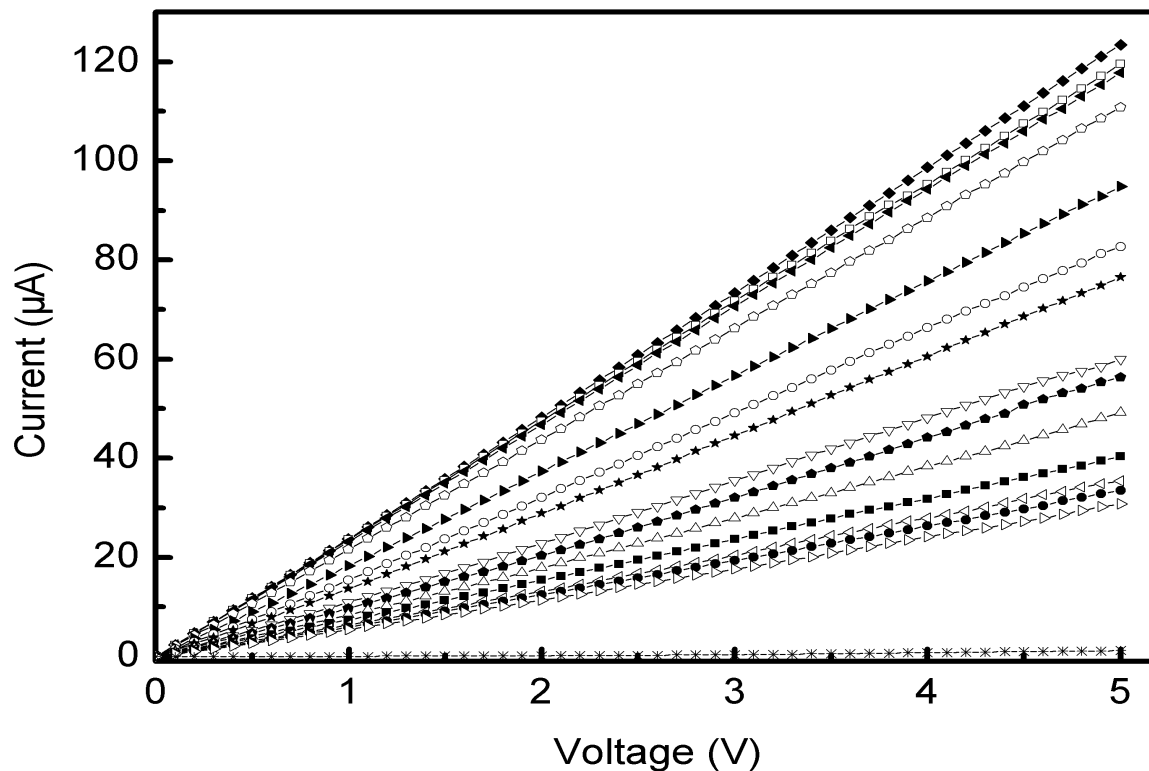
# I-V Measurements of Strained ZnO Nanowires

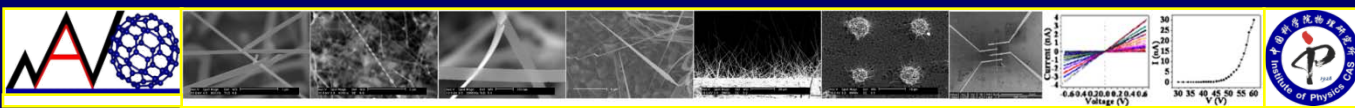




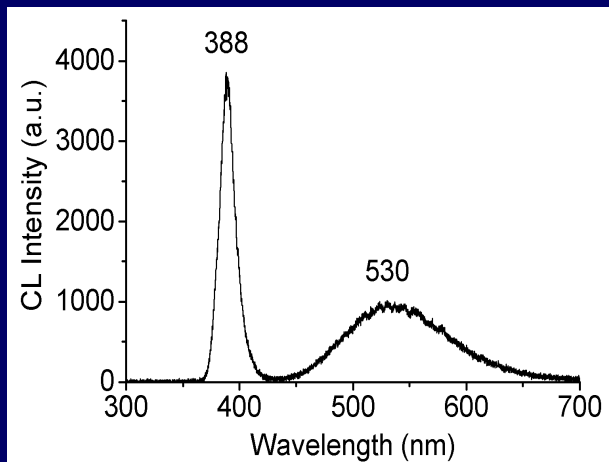


# I-V Properties of A Strained Nanowire during Bending Process

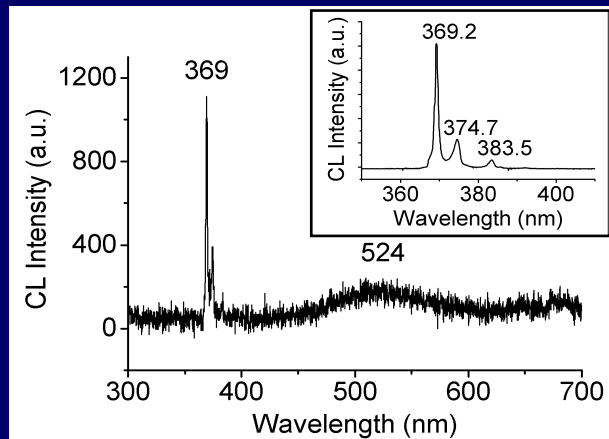




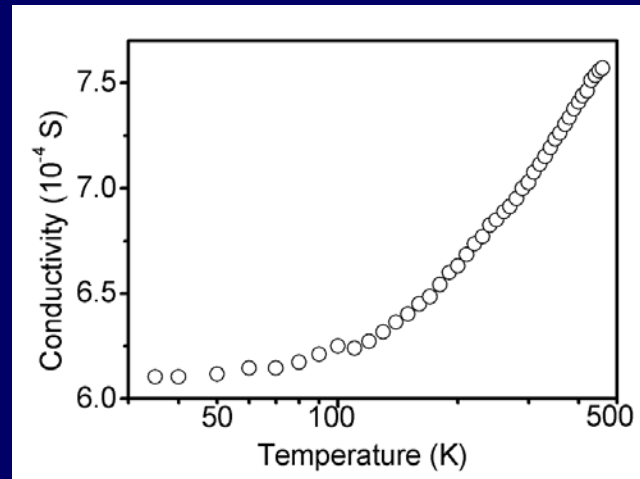
# CL Property and Temperature- Conductance Relationship Of ZnO Nanowires



Room temperature (300K)

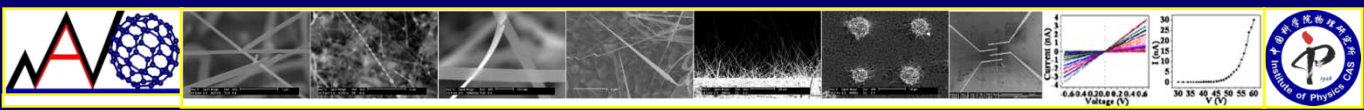


Low temperature (30K)



- ❖ Strong emission of green-light
- ❖ High electrical conductance
- ❖ Slight change during T change
- ❖ R is proportional to  $\ln T$  at LT

2D metal-like characteristic



# Theoretical Considerations

Weak localization:  $R \propto -p \ln T$

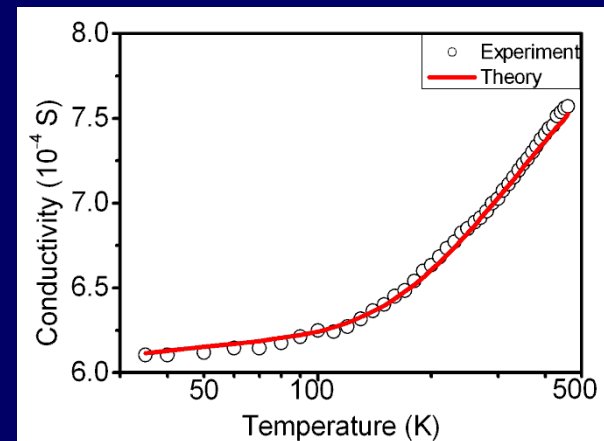
$$\sigma = \alpha \ln T + \frac{\beta}{1 + \exp(\Delta E / K_B T)} + \gamma \quad \left( \alpha = \frac{e^2 p}{\pi h} = 1.2 \times 10^{-5} \times p \right)$$

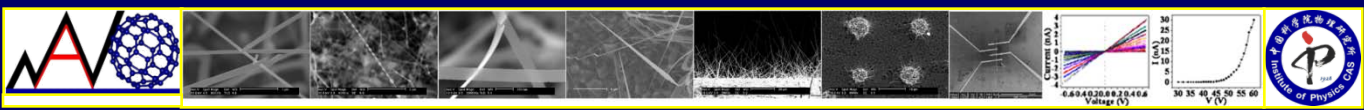
$$\sigma = 1.0 \times 10^{-5} \ln T + \frac{0.00048}{1 + \exp(530.2 / T)} + 0.00056$$

$$\alpha = 1.0 \times 10^{-5}$$

$$\Delta E = 45.7 \text{ meV}$$

X. Lin/H.J. Gao et al., APL 2007

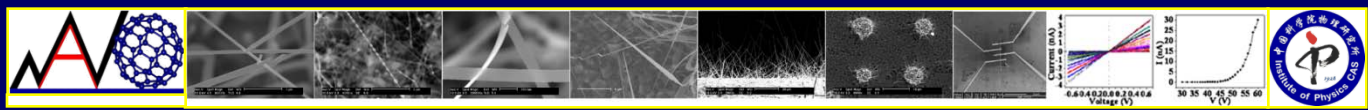




# OUTLINE

- Introduction
- Four Probe STM Setup: Imaging and I-V Measurements
- **Boron Nanostructures: synthesis and characterization**
- Properties of Boron Structures: electrical, mechanical and field emission
- Conclusions





# Experimental Details: Thermo-reduction of boron-oxygen compounds with active metal

**Precursors:** B, B<sub>2</sub>O<sub>3</sub> and Mg

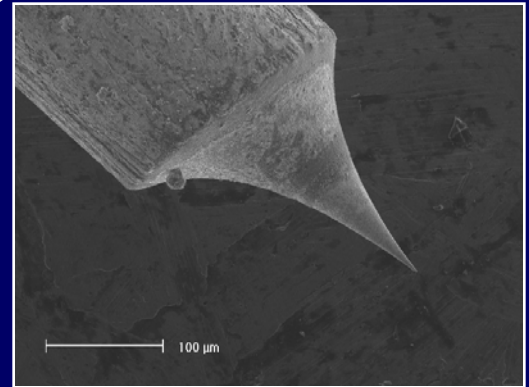
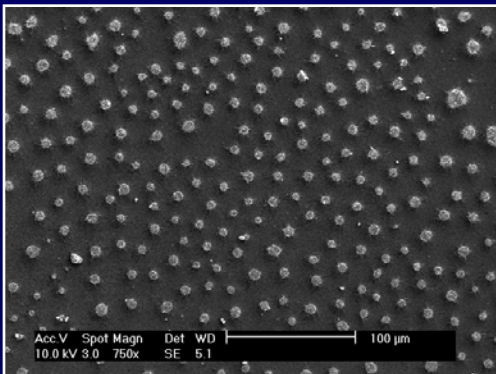
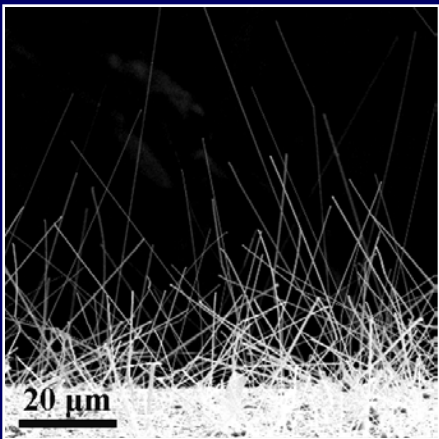
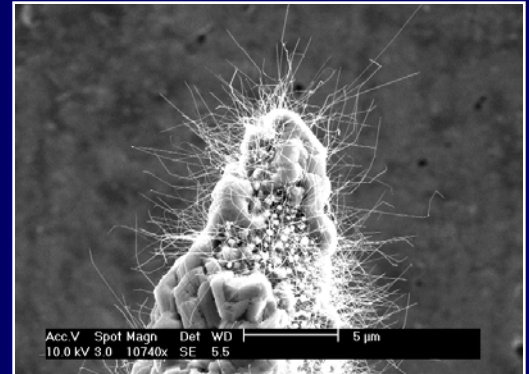
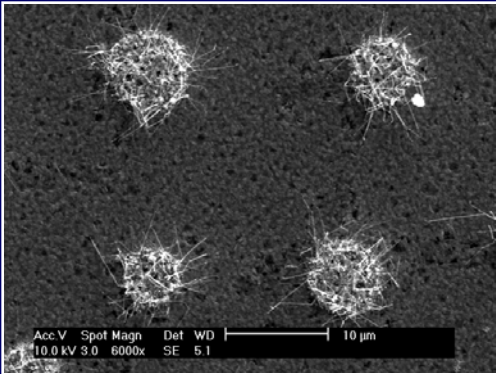
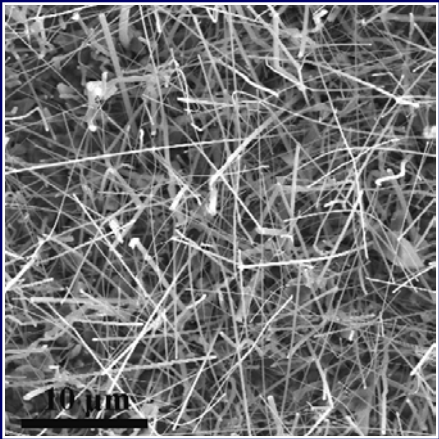
**Catalyst:** Fe<sub>3</sub>O<sub>4</sub> nanoparticles

**Substrate:** Si (111) and STM tips

**Carrier gases:** 5 ~ 10% H<sub>2</sub>/Ar

**Reaction temperature:** 400 °C for 30 min ; 1100 ~ 1200 °C for 2 h

# Controllable Growth of Boron Nanowires

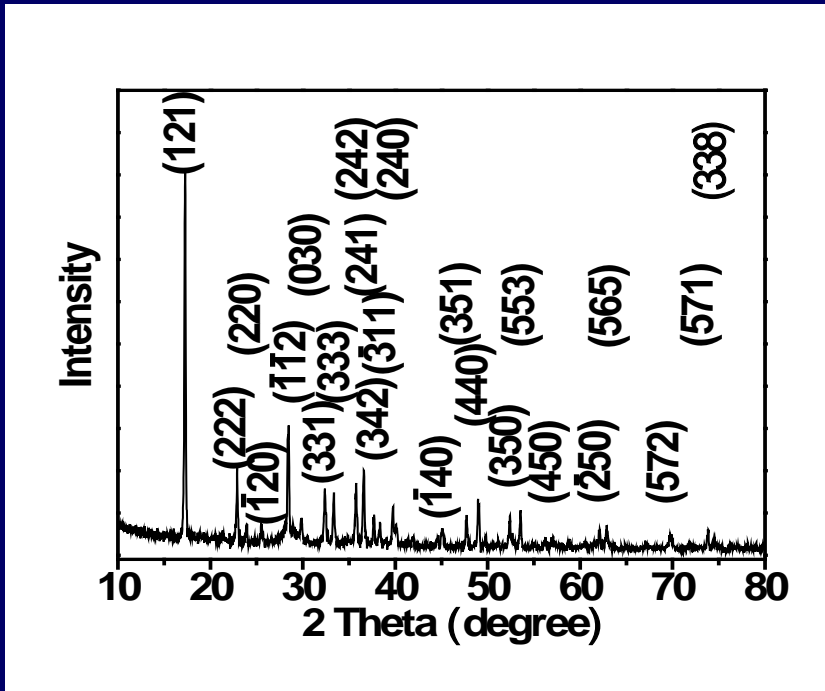
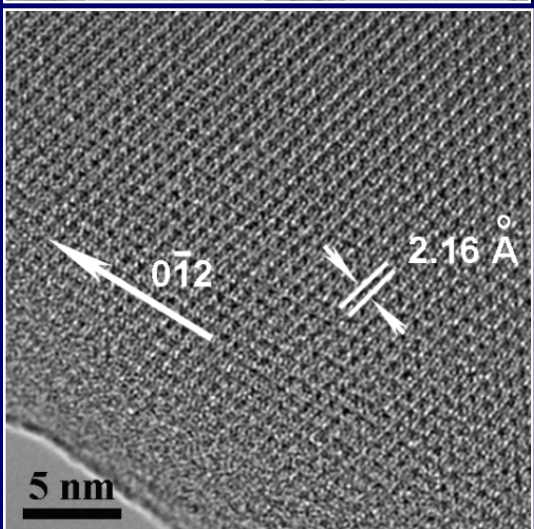
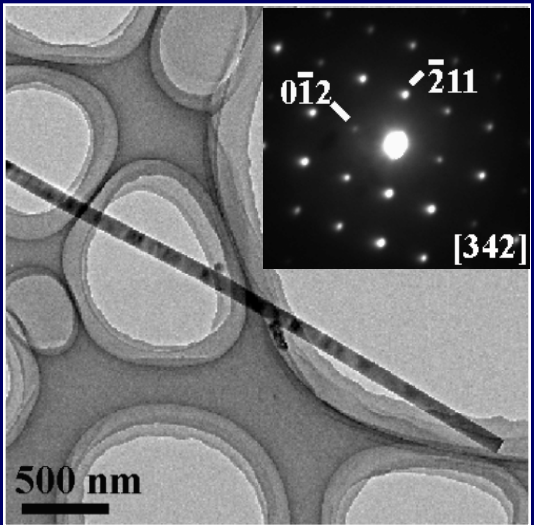


High density

Pattern

STM tip

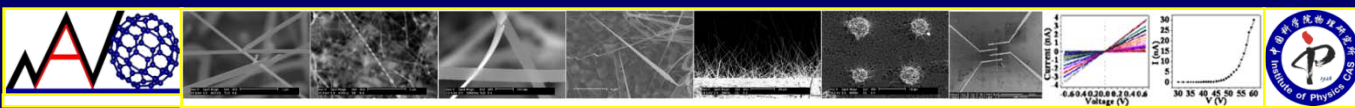
# Structures of Boron Nanowires



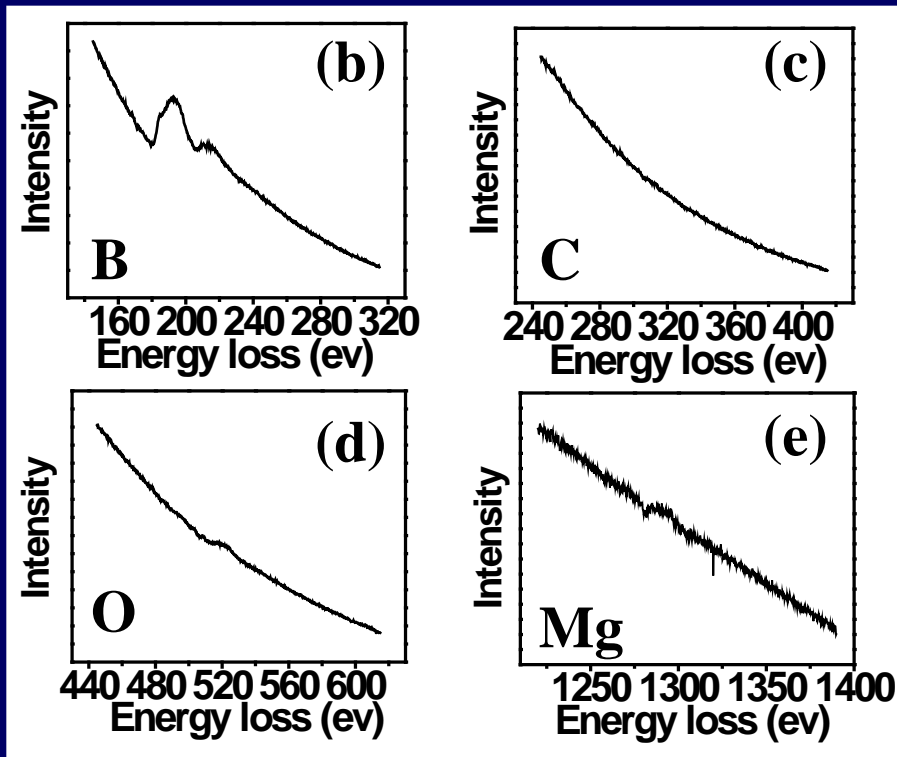
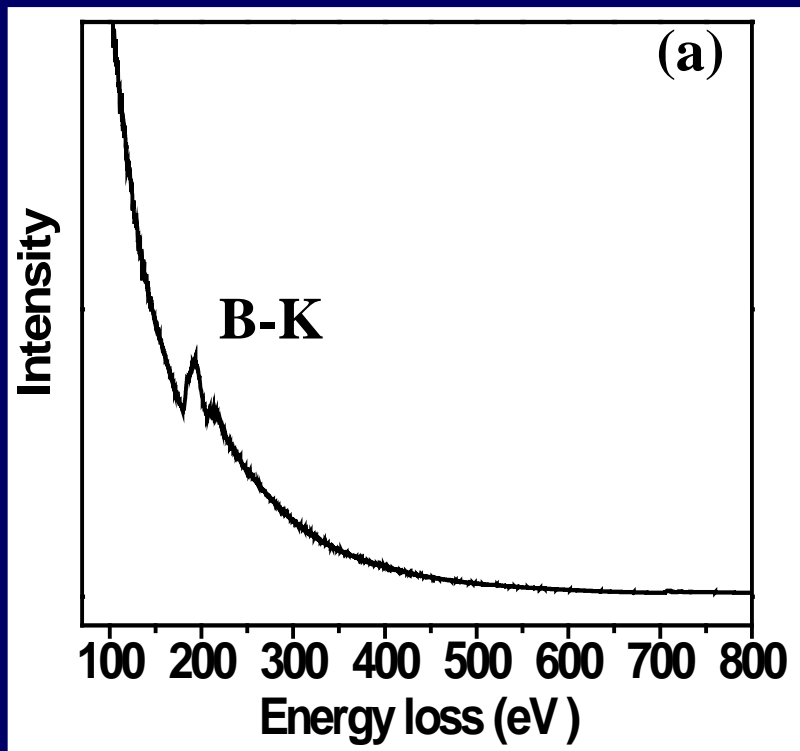
$\beta$ -rhombohedral : JCPDS : 85-0409

$a=b=c=10.17 \text{ \AA}$  ;  $\alpha=\beta=\gamma=65.12^\circ$

- Diameter: 50-200nm
- Rhombohedral structure
- Length up to several  $\mu\text{m}$
- Growth direction  $[0\bar{1}2]$



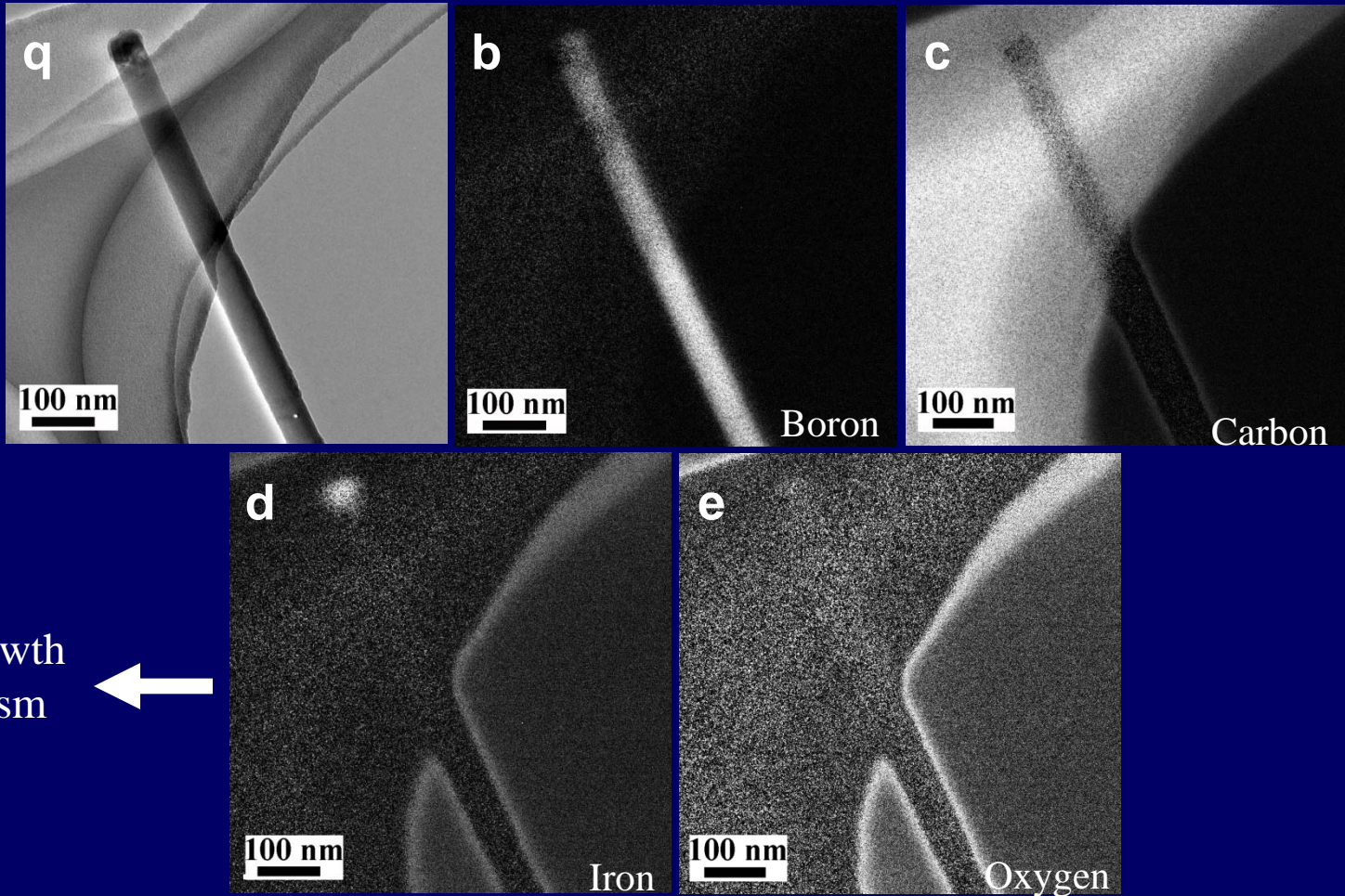
# The Composition of Boron Nanowires



a) A typical EELS spectrum from individual nanowire; b) K-shell ionization edge of the boron is clearly seen at about 188 eV; c, d, e) The EELS for possible impurities of carbon (284 eV), oxygen (532 eV) and magnesium (1305 eV), respectively.

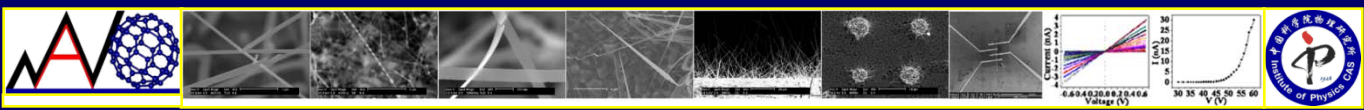


# The EFTEM Image of Boron Nanowire



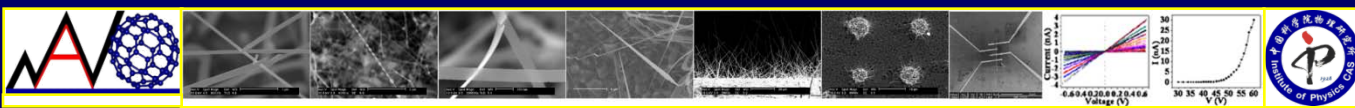
VLS growth mechanism

a) Typical TEM image of boron nanowire; Elemental mappings of b) boron, c) carbon, d) iron and e) oxygen.

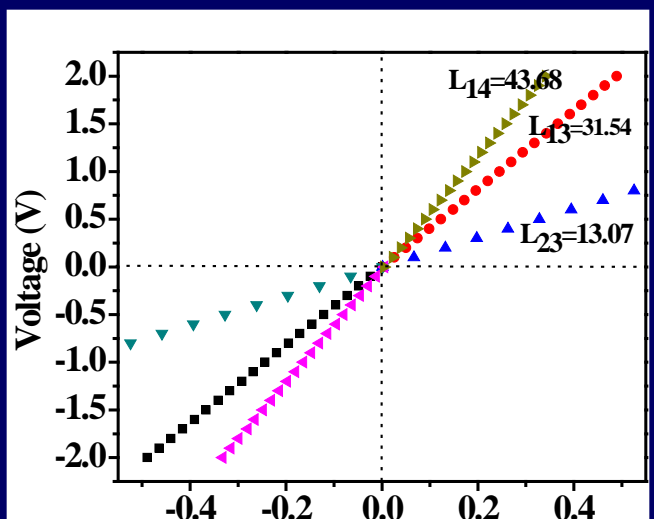


# OUTLINE

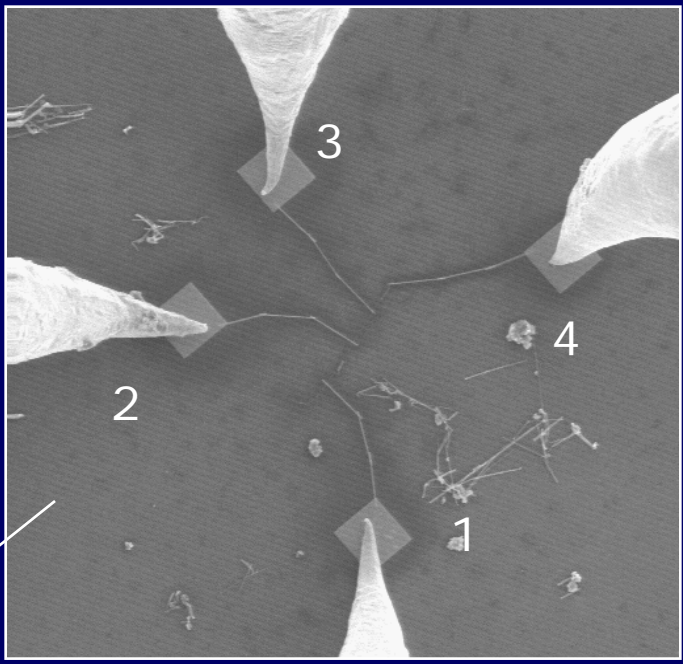
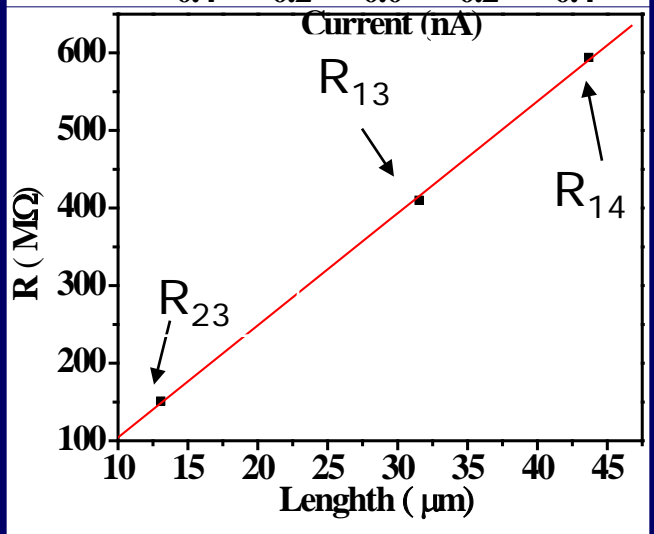
- Introduction
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# I-V characteristics : Ohmic contact (two terminal measurement -23,13,14) (Electrodes are Pt)



$L_{23} = 13.07 \mu m$   
 $L_{13} = 31.54 \mu m$   
 $L_{14} = 43.68 \mu m$   
 $D = 200nm$



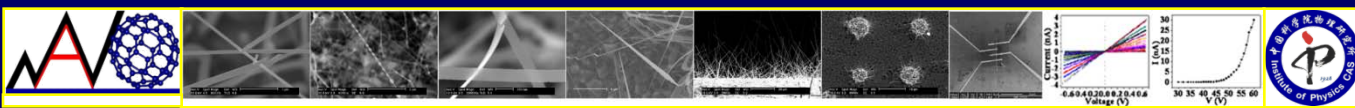
Made by FIB

10kV, 250μm×250μm

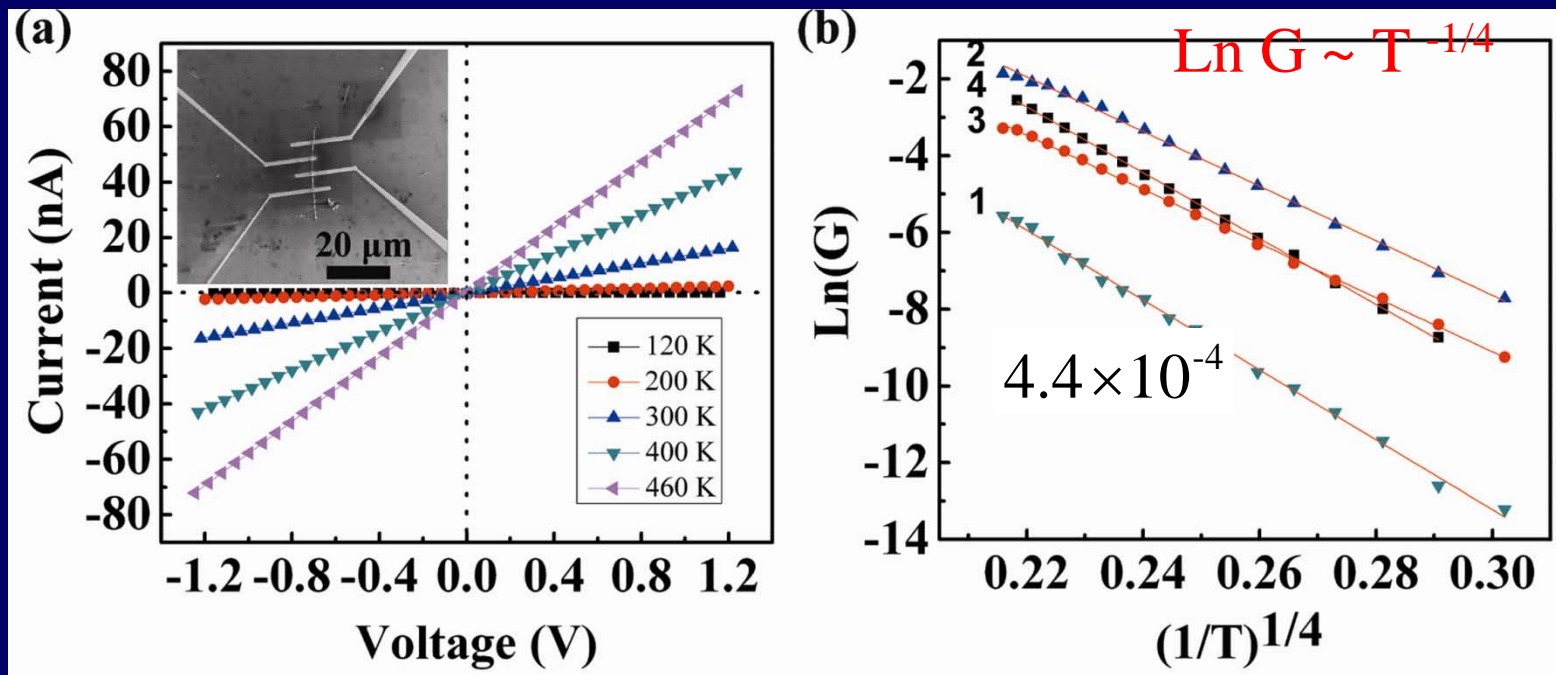
Work function:  $\Phi_{Pt} = 5.3eV > \Phi_B = 4.3eV$

B NW has Ohmic contact with Pt  
 B is a p-type semiconductor





# The Temperature Dependent Behavior of B NWs



Mott's law

$$G = G_0 \exp \left\{ - \left( \frac{T_0}{T} \right)^{1/4} \right\}$$

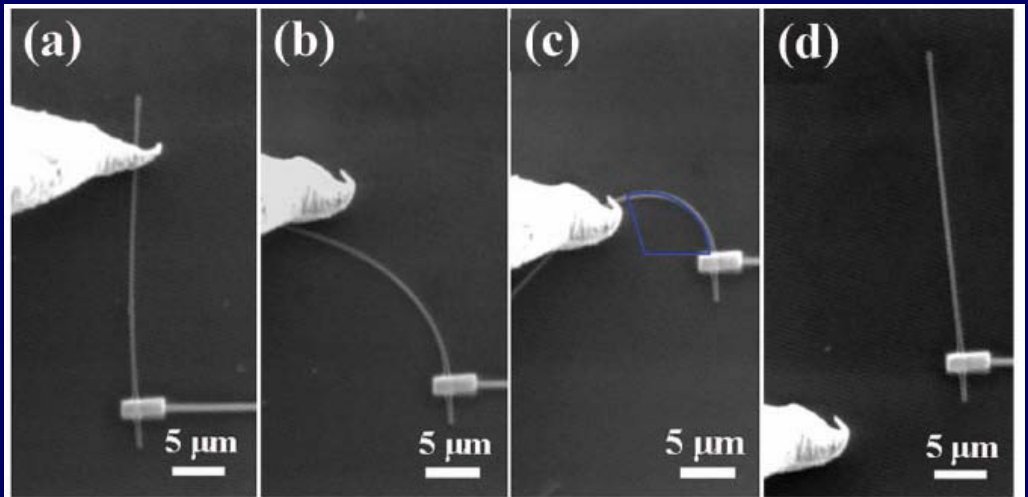
$$T_0 = \frac{60}{\pi k_B \ell^3 N(E_F)}$$

for the three-dimensional VRH

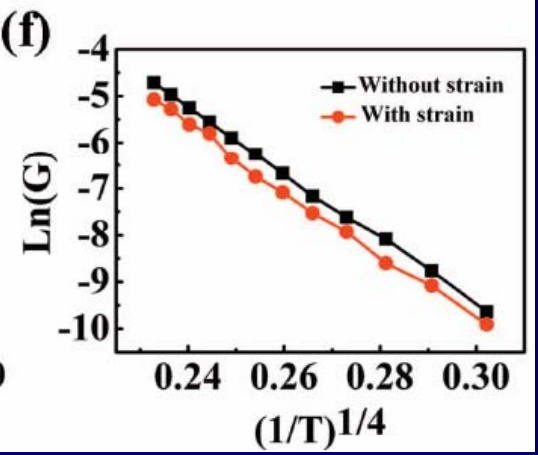
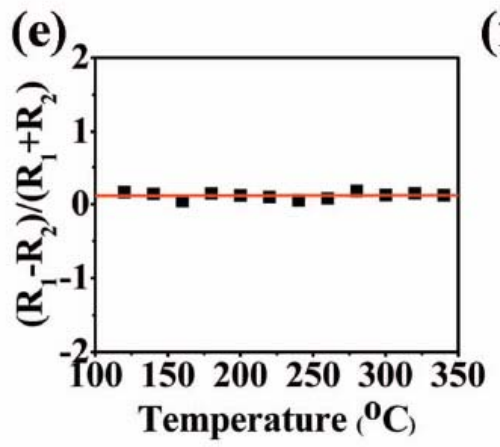
$T_0$  of the four devices

sample	$\beta$ -rh. B (polycrystalline)	$\beta$ -rh. B (single-crystal)	Device 1	Device 2	Device 3	Device 4
$T_0$ (K)	$5.1 \times 10^9$	$8.7 \times 10^7$	$6.8 \times 10^7$	$2.56 \times 10^7$	$2.47 \times 10^7$	$5.4 \times 10^7$

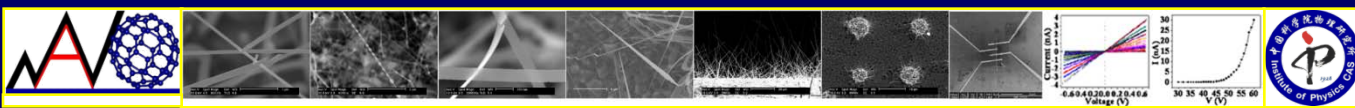
# Robust Conductance and Flexibility of B NWs



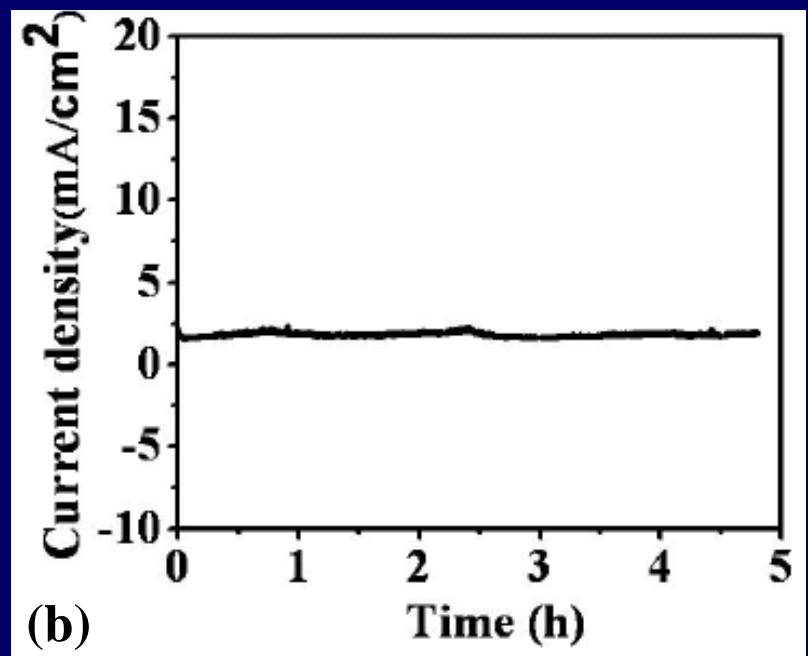
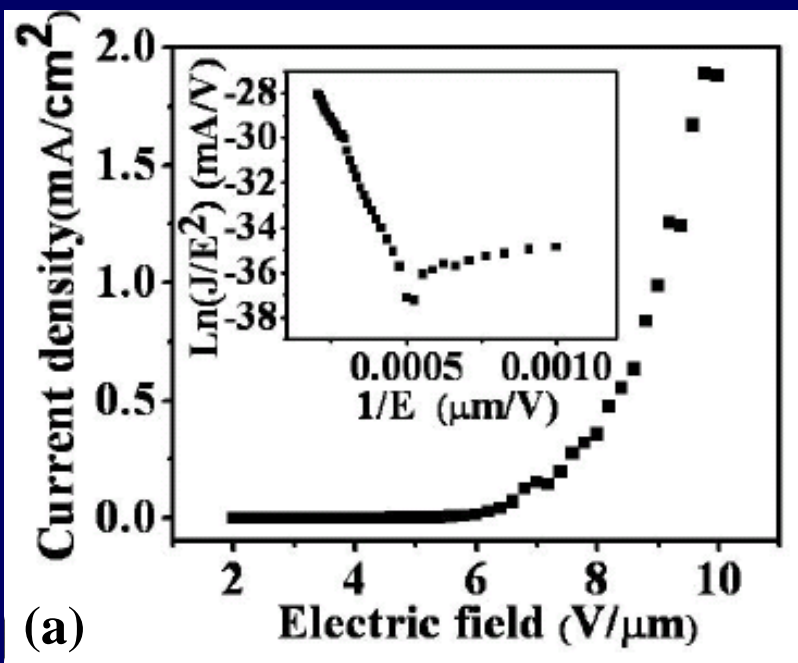
- a)  $\rho=139.3\Omega\cdot\text{cm}$ , effective length  $L_{\text{effect}}=23.45\ \mu\text{m}$ , diameter  $d=150\ \text{nm}$ .
- b)  $\rho=143.8\ \Omega\cdot\text{cm}$ ,  $L_{\text{effect}}=20.08\ \mu\text{m}$ .
- c)  $\rho=142.4\Omega\cdot\text{cm}$ ,  $L_{\text{effect}}=20.44\ \mu\text{m}$ , and the distortion of the nanowire is 3%.
- d) After releasing the strain.
- e)  $R_1-R_2 / R_1+R_2$  vs  $T$ , where  $R_1$  and  $R_2$  are the resistances of boron nanowire without and with 3% strain
- f) Temperature dependence.







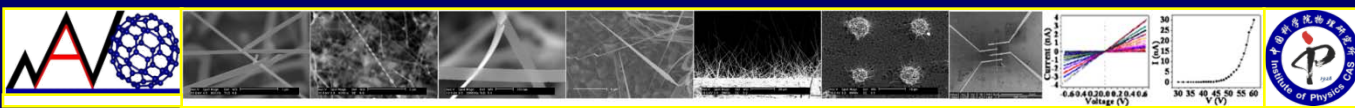
# Field Emission---High Density B NWs Film



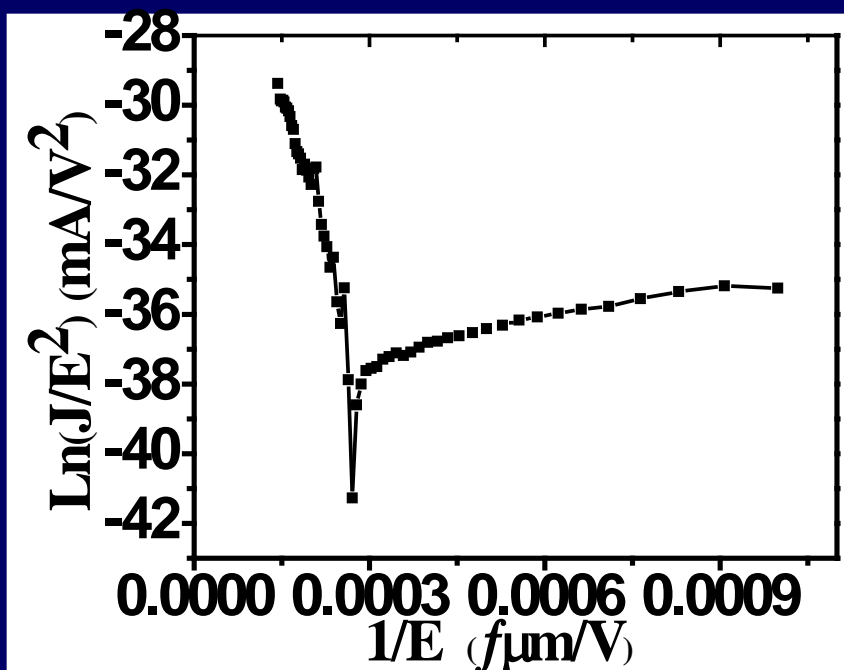
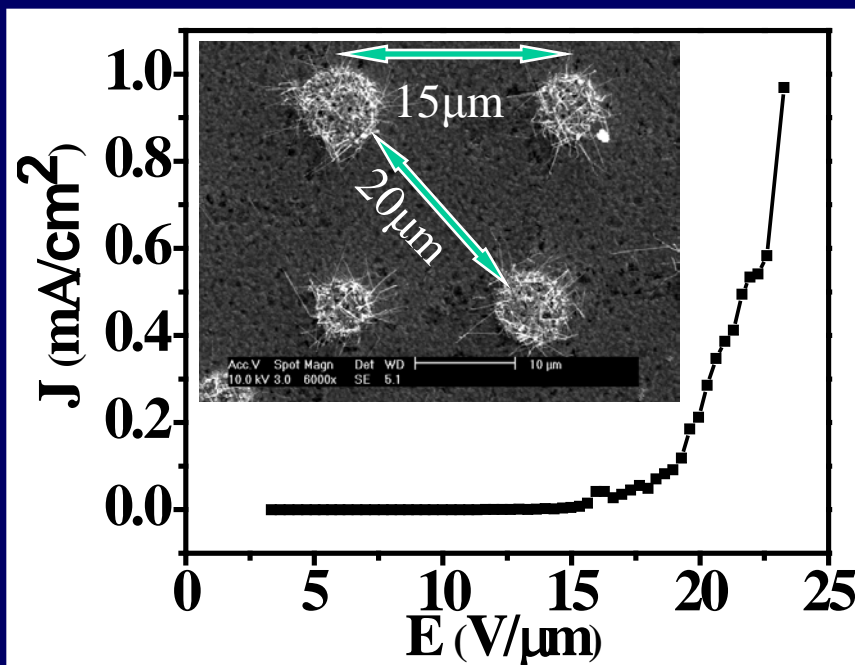
Turn-on Field : the applied field when the emission current gets to  $10\mu\text{A}/\text{cm}^2$ .

Threshold Field : the applied field when the emission current gets to  $1\text{ mA}/\text{cm}^2$ .

	B nanocone	AlN nanocone	CNT
$E_{\text{on}}=5.7\text{ V}/\mu\text{m}$	$3\text{ V}/\mu\text{m}$	$12\text{ V}/\mu\text{m}$	$2.5\text{ V}/\mu\text{m}$
$E_{\text{th}}=9\text{ V}/\mu\text{m}$	$5.3\text{ V}/\mu\text{m}$		



# Field Emission of Patterned B NWs Film



Patterned Boron (PB)  $\left\{ \begin{array}{l} E_{on} : 15 \text{ V} / \mu\text{m} \\ E_{th} : 22.5 \text{ V} / \mu\text{m} \end{array} \right.$ 
 High density Boron (HB)  $\left\{ \begin{array}{l} E_{on}=5.7 \text{ V} / \mu\text{m} \\ E_{th}=9 \text{ V} / \mu\text{m} \end{array} \right.$

Length of B NW:  $L=5 \mu\text{m}$   
 Distance of patterns:  $D=15-20 \mu\text{m}$

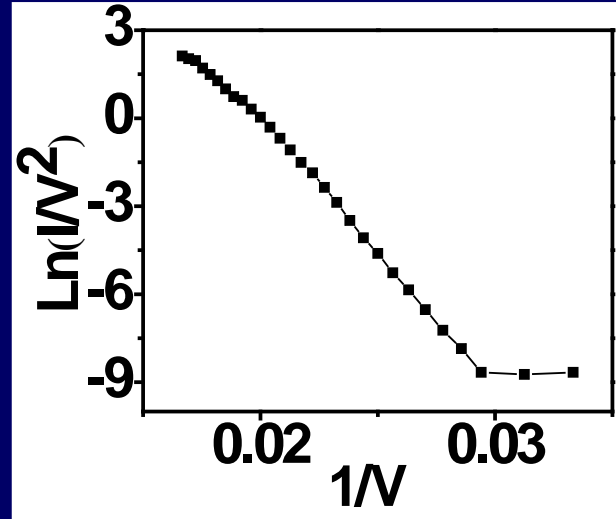
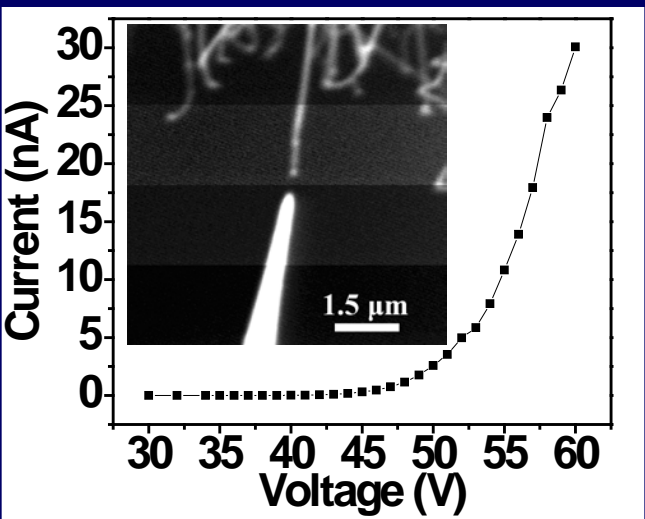
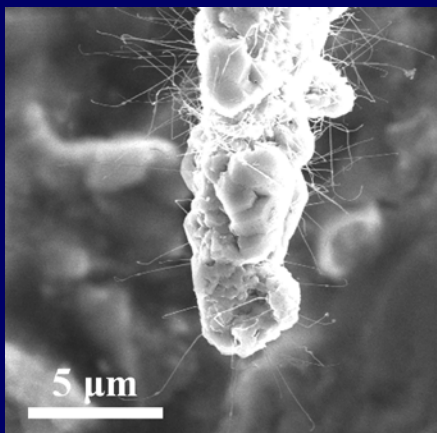
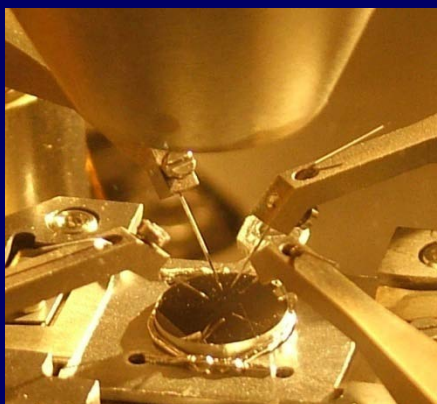
}  $D / L=3, 4$

**PB: HB**

Desity: 1 : 10

FE: 1 : 2.6

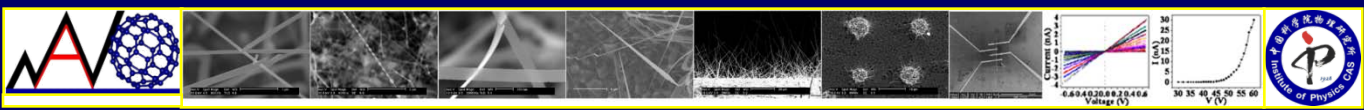
# Field Emission Properties of A Single B Nanowire



Emission current density:  $10^4 \text{ A/cm}^2$  at 60 V

Turn on field : 70 V/  $\mu\text{m}$  at 500 nm

- Single carbon NT:  $10^4 \sim 10^6$
- ZnO nanowire:  $10^2 \sim 10^3$
- LaB<sub>6</sub> NW:  $10^3 \sim 10^4$

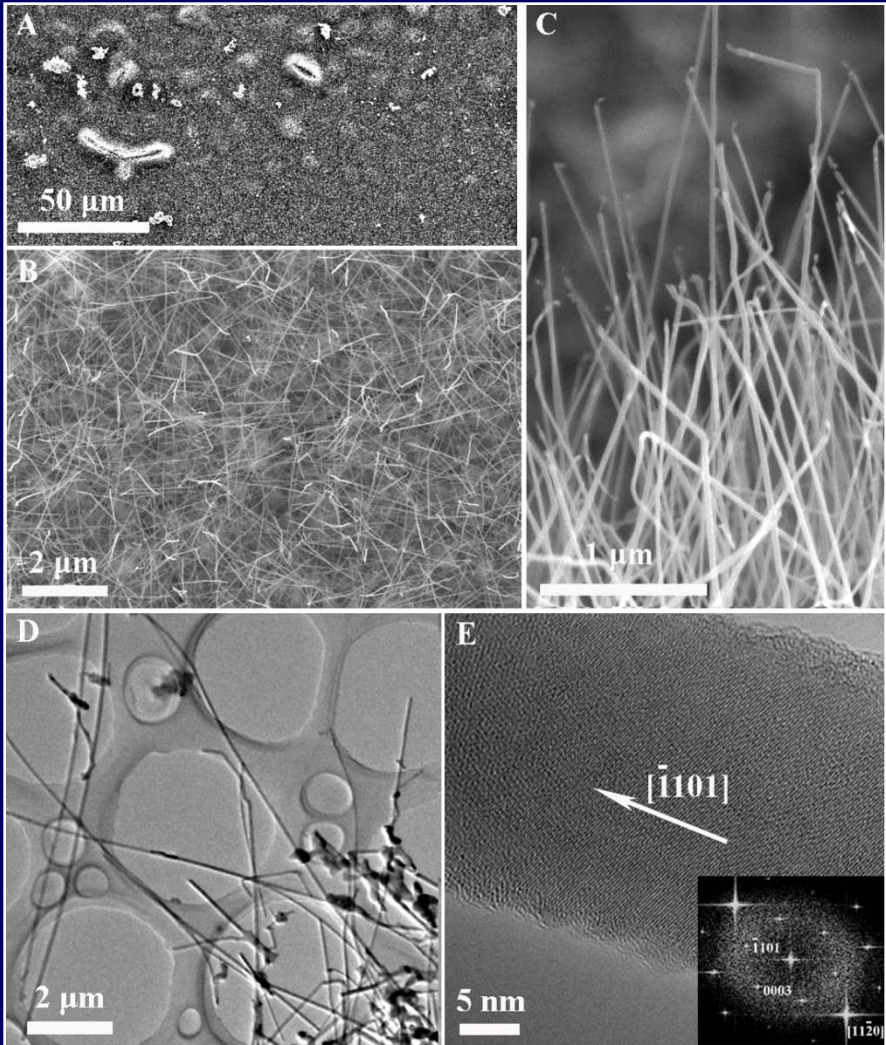


# OUTLINE

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- **Properties of Boron Carbide NanoStructures: electrical, mechanical and field emission**
- Conclusions

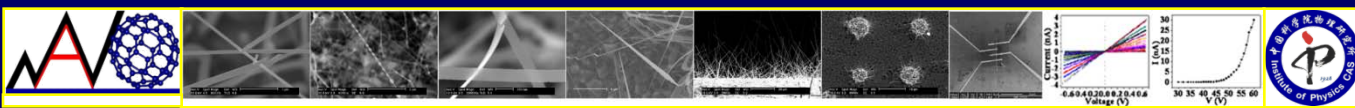


# SEM and TEM Structure of B<sub>4</sub>C Nanowires

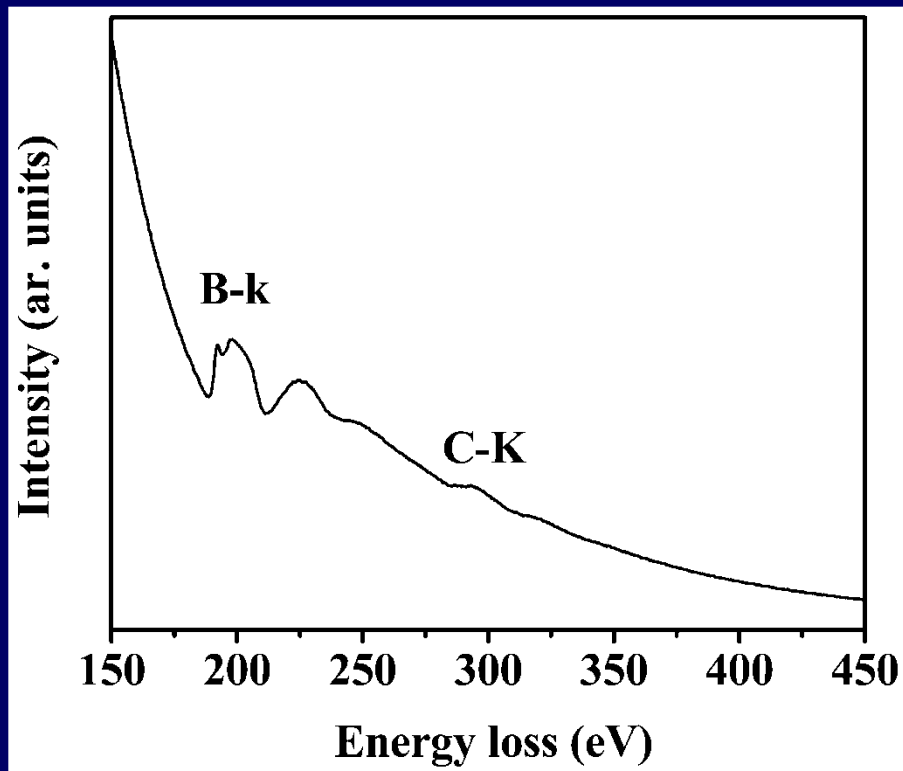


- A) The SEM image of large-scale boron carbide nanowires.
- B) The SEM image of high density boron carbide nanowires with higher magnification.
- C) The side-view SEM image showing some protrusions of boron carbide nanowires.
- D) The TEM image of boron carbide nanowires.
- E) The HRTEM image of boron carbide nanowire, the inset is the corresponding FFT pattern from the HRTEM image; 4). Nanowires.



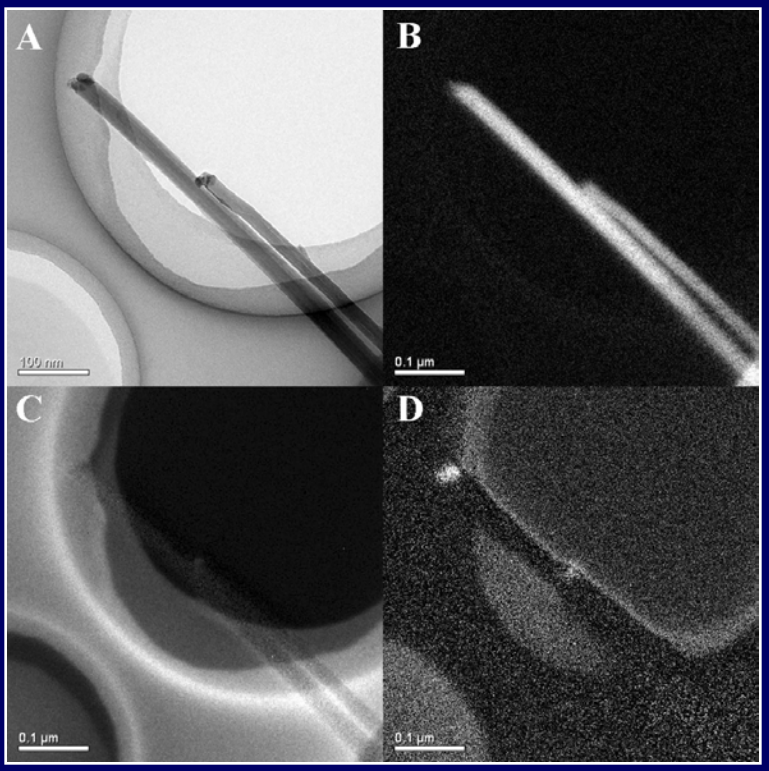


# Composition and Distribution of B<sub>4</sub>C nanowires



The EELS from Boron carbide nanowire showing characteristic B and C K-edges at 188 eV and 284 eV.

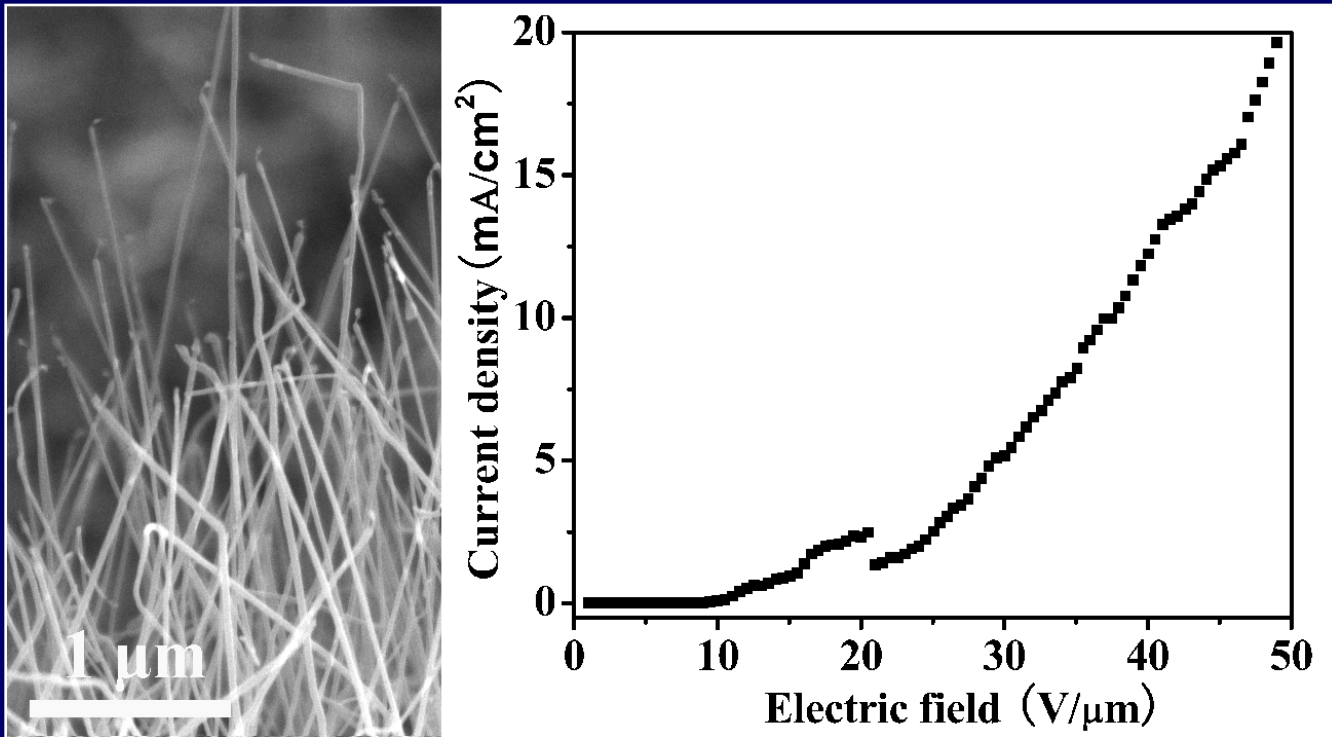
$$B : C = 4.08$$



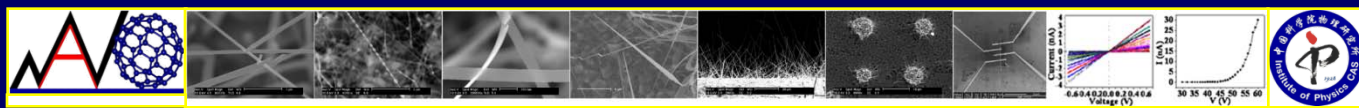
(A) TEM image. (B) The mapping image of boron. (C) Carbon. (D) Iron.

VLS growth mechanism

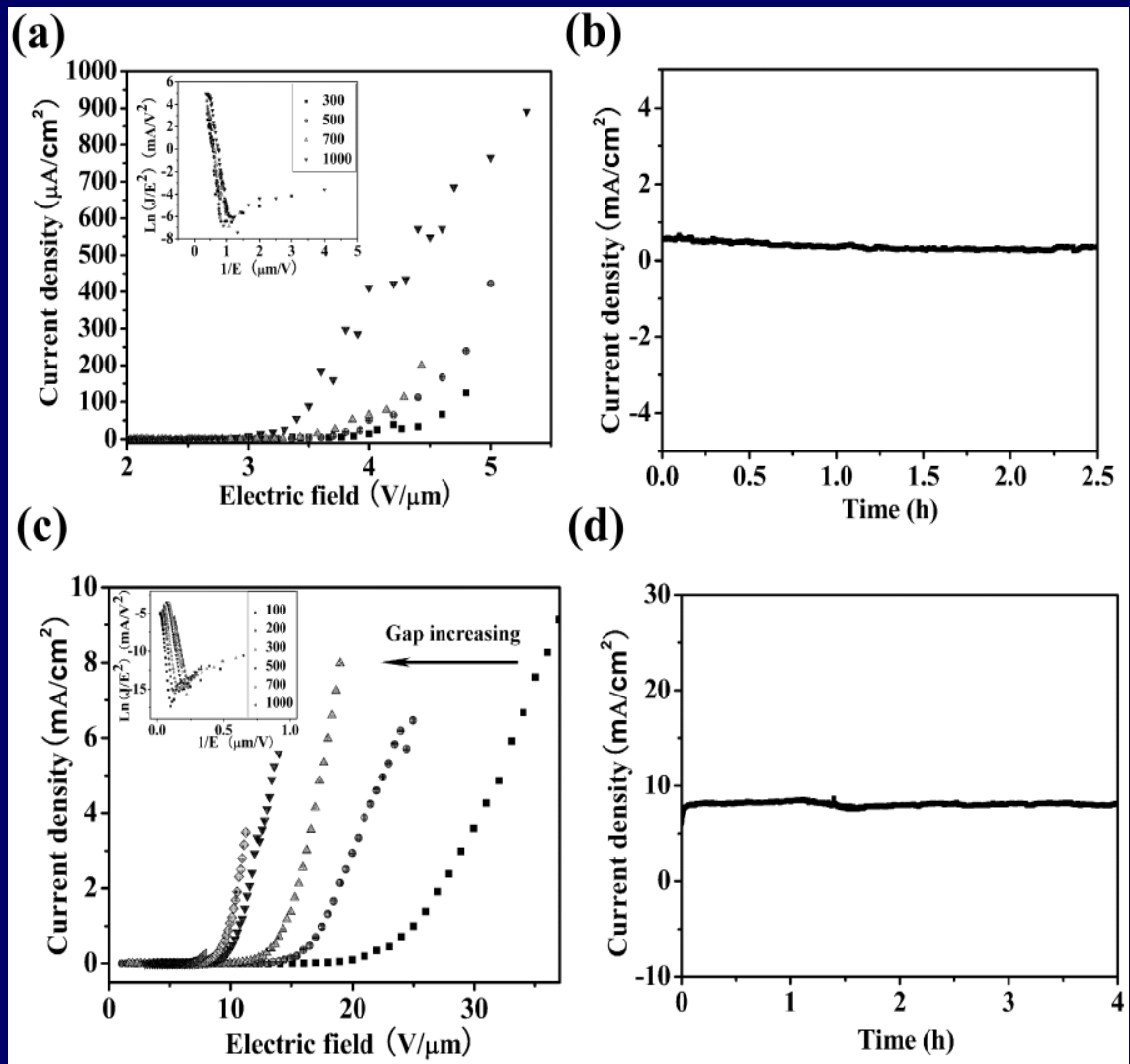
# Field Emission Property of B<sub>4</sub>C Nanostructure Films



The FE current density ( $J$ ) is turned on at 4.0 V/μm and steadily increases to 2.48 mA/cm<sup>2</sup> at 20.6 V/μm. Then it experiences a sudden drop to 1.43 mA/cm<sup>2</sup> when the applied field ( $E$ ) passes 20.6 V/μm.



# Field Emission Property of B<sub>4</sub>C Nanowire Films



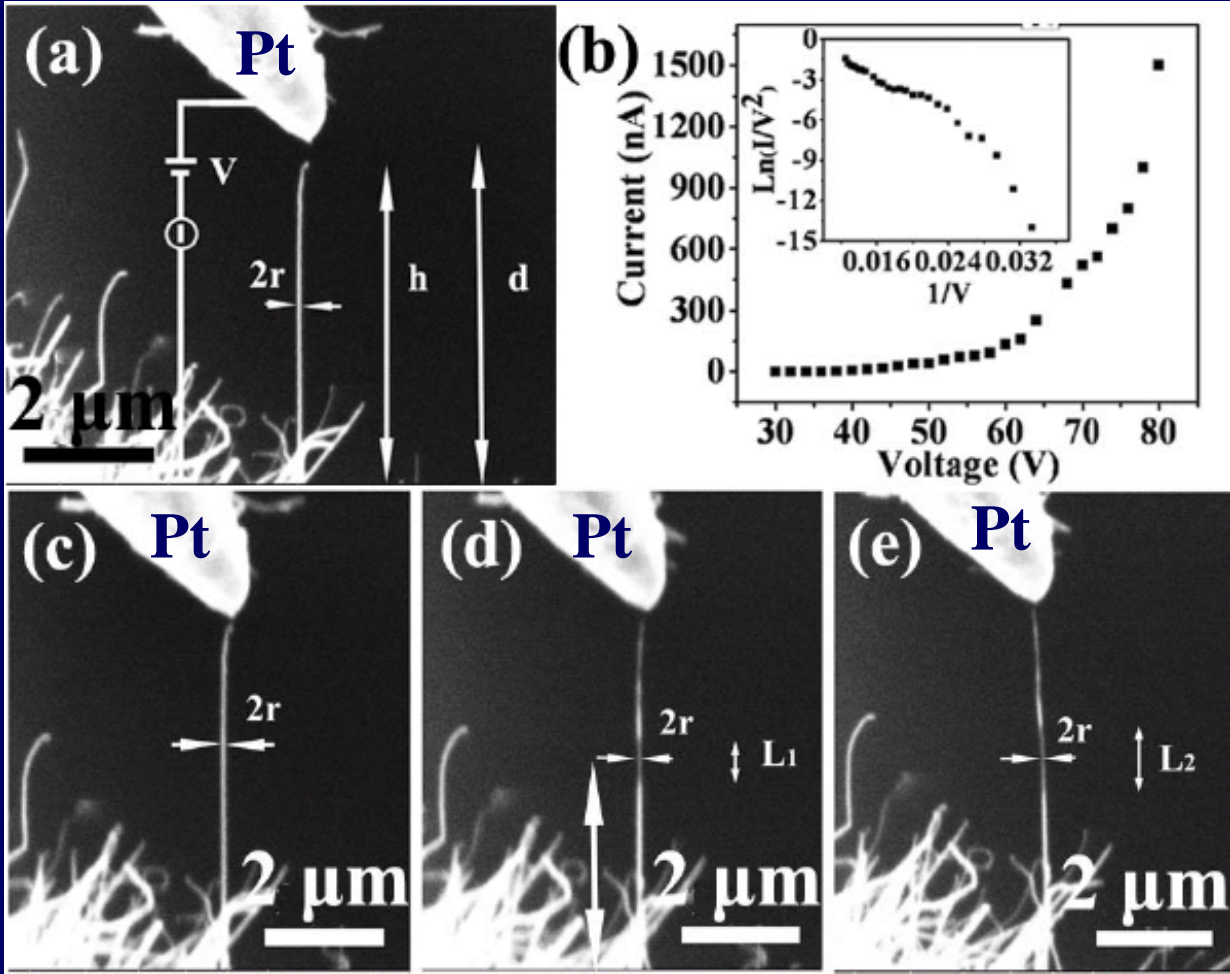
The turn-on field was decreased from **3.8 V/μm** to **3 V/μm** corresponding to the vacuum gaps increased from 300 μm to 1000 μm. The current fluctuation is less than **9%**.

The turn-on fields decreases (16 V/μm to 6.3 V/μm) with increasing vacuum gaps (100 μm to 1000 μm).

The high field emission current of B<sub>4</sub>C nanowires is very stable with fluctuation below **5%**.

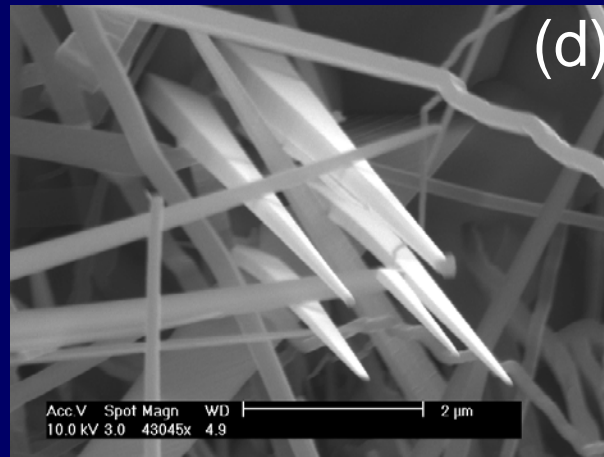
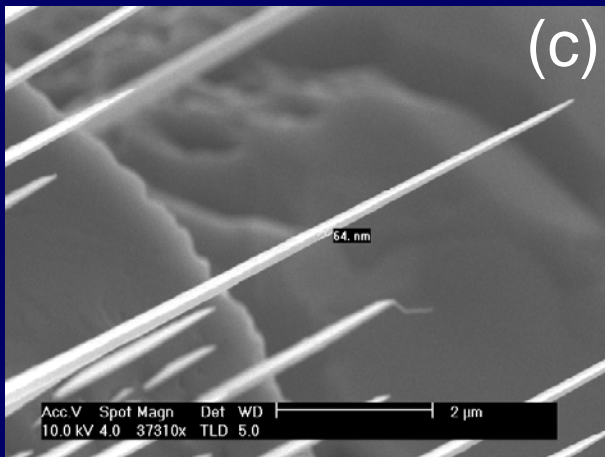
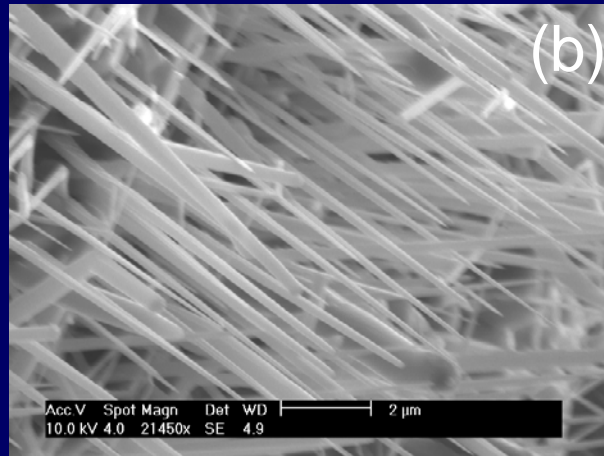
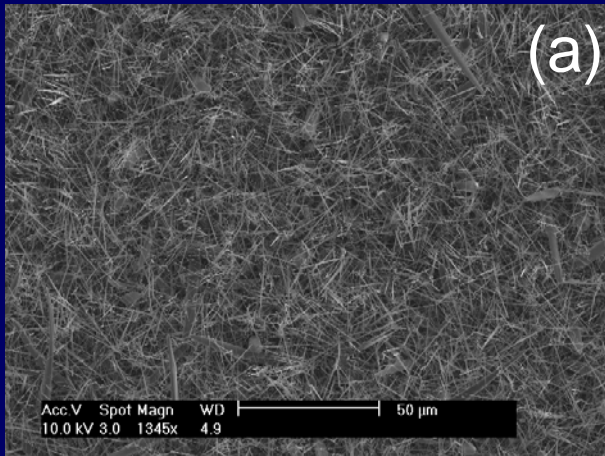
There is no current decline during a long-term emission.

# Field Emission Property of a Single B<sub>4</sub>C Nanowire





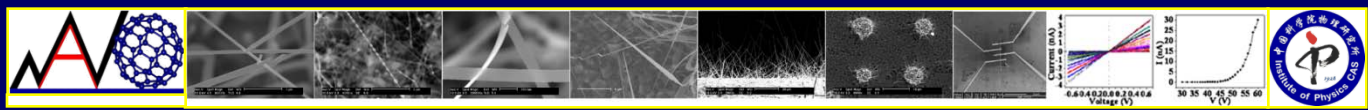
# Boron Nanoswords: Growth and Properties



- 1) 400°C , 0.5h ,  
8.0X10<sup>2</sup> Pa ;
- 2) 1200°C , 2h ,  
5.5X10<sup>3</sup> Pa 。

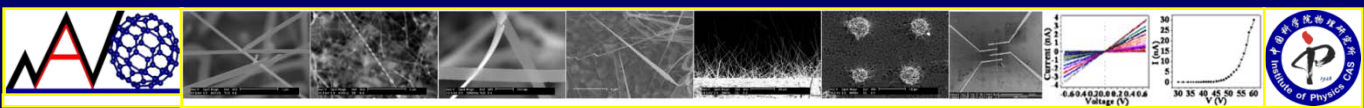
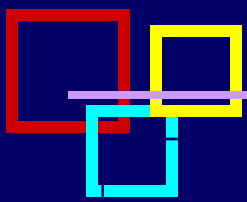
- 10-5 nm
- Thickness:  
a few tens nm





## Conclusions

- We have developed a novel synthetic route for controllable growth of high quality boron nanowires.
- The electrical transport of single boron nanowires shows room temperature conductivity of  $4.4 \times 10^{-4} (\Omega \cdot \text{cm})^{-1}$ , and follows the Mott's VRH mechanism. This electrical conductivity is very robust under mechanical strain up to 3% which indicated that boron nanowires show excellent flexibility.
- FE characteristic of boron nanowires film, patterned boron nanowires film and a single boron nanowire reveal a high field emission current density from them. Boron nanowire material is a good candidate for field emission applications.



# Acknowledgements

L. Gao, Y.L. Wang, X. Lin, Y. Pan, Q. Liu, H.G. Zhang, Z.T. Deng, Z.H. Cheng, X.B. He, W. Ji, S.X. Du, C.M. Sheng, D.X. Shi, and .....  
IOP CAS, China

Feng Liu, *Utah U., USA*

Qian Niu, *UT-Austin, USA*

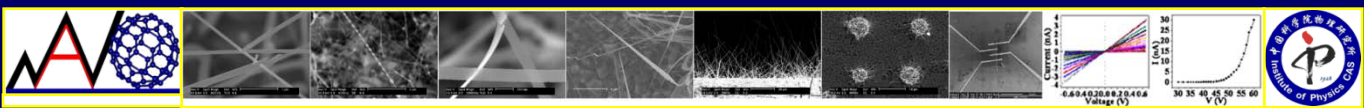
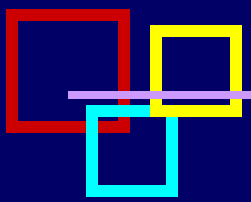
X.C. Xie, *IOP/ASU*

Werner Hofer, *Liverpool Univ., UK*

Hong Guo, *Mcgill U., Canada*

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Thank you for your attention!